# Spectral characterization of solid-state laser-driven plasma sources of EUV light

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## Spectral characterization of solid-state laser-driven plasma sources of EUV light

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Cover: Spectral emission of tin plasma in the extreme ultraviolet regime calculated for optical depths of 0.2, 0.7, 2, 4.5, 10, 20 and 40 (solid lines) and for a blackbody of 34 eV temperature (dotted line). The spectra shown are produced by applying the one-dimensional radiation transport model described in Chapter 4 to an experimentally recorded spectrum where a tin microdroplet was irradiated by a  $2-\mu$ m-wavelength laser pulse.

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### Introduction

Microelectronics, especially in the form of integrated circuits, has become an essential part of our everyday lives, be it in the form of consumer electronics such as smart phones and personal computers, or in bigger settings such as computer clusters used, e.g., for weather forecasting or to power search engines. The groundbreaking innovation making all of these applications possible was the transistor, a device proposed by J.E. Lilienfeld in the early twentieth century [1, 2]. In 1947, a first working device was built in the form of a point-contact transistor [3]. The extreme miniaturization of electronics over the last few decades was later made possible by introduction of the metal–oxide–semiconductor field-effect transistor (MOSFET). This device, invented in 1959, allowed for mass-production and efficient size reduction via photolithography [4].

In photolithography (referred to in the following as simply 'lithography'), light is used to imprint a pattern encoded on a mask onto a substrate. The mask is illuminated either in reflection or transmission after which the light is imaged onto a silicon wafer coated with a photoresistive chemical. Upon illumination, the structure of the chemical is altered and in subsequent processes the excess material is removed, leaving behind the printed structure. Over the years, the development of new complex techniques enabled the continued shrinkage of printed feature sizes while lithography continued to be the underlying production method. The progressive miniaturization of printable features is commonly gauged by the number of transistors printed per unit area. The latter was predicted by G.E. Moore to roughly double every two years, while the cost per transistor was predicted to approximately halve within the same time period [5, 6]. These predictions were closely followed by the semiconductor industry for several decades [7].

One of the main enablers for this achievement has been the use of ever-shorter wavelength light in the lithography process. While first lithography machines used light from mercury lamps of approximately 400 nm wavelength, these lamps were soon replaced by shorter-wavelength laser sources operating in the deep-ultraviolet (DUV) spectral regime in order to increase printing resolution. Following Abbe's resolution limit, the smallest feature size which can be printed, the so-called critical dimension (CD), is given by  $CD = k_1 \lambda/NA$ . The CD clearly scales with the wavelength  $\lambda$  of the light source. The remaining factors are the numerical aperture (NA)

of the illumination system and a production process specific constant  $k_1$ , typical values in DUV lithography systems being 0.3-0.4 [8], and are relatively more limited in their optimization. Nevertheless, after the introduction of ArF excimer lasers as light source at a 193 nm wavelength, the resolution scaling via wavelength came to an abrupt halt because of a lack of economically feasible high-power light sources at shorter wavelengths as well as increased difficulties arising from the strong absorption of shorter wavelength light by virtually all materials. These constraints made DUV lithography the standard for more than two decades and creative techniques were developed to continue the miniaturization of printable structures [8]. One important achievement towards further miniaturization was the increase of the system NA by insertion of a liquid with refractive index n > 1 between the illumination optics and the wafer. Another important advancement was the introduction of so-called multi-patterning, the process by which multiple illumination cycles are used to print a single structure. Nowadays, the technique of multi-patterning enables the printing of features well below the resolution limit of DUV lithography systems. The use of multi-patterning does however significantly increase the amount of production steps and in turn the cost per transistor. Hence, a new technological breakthrough was needed: lithography in the extreme ultraviolet (EUV) spectral region.

Using a shorter 13.5-nm wavelength, the printing resolution of ASML's lithography systems has further improved and the proposed high-NA imaging systems (NA = 0.55) will enable the introduction of 3 nm nodes within the next years [8, 9]. One of the main reasons for the choice of 13.5-nm light is the good reflectivity of producible multilayer optics at this wavelength which efficiently reflect in a 2% bandwidth around said wavelength, the so-called *in-band* region [10]. After deciding on an appropriate light source wavelength, the type of light source had to be chosen. Consideration was given to free-electron lasers, laser-produced plasmas (LPPs) or discharge produced plasmas. Based on factors including required EUV power, source up-time and assessment of financial risks, LPP sources using masslimited targets eventually became the light source of choice. In these LPP sources, tin microdroplets are irradiated in a two-pulse scheme. First, a low-intensity prepulse propels and deforms the droplets into extended targets. These targets are subsequently illuminated by a second high-intensity pulse to create a hot, EUVemitting tin plasma [11]. Tin was chosen over other elements, such as lithium, because a plethora of its charge states emit strongly at 13.5 nm, promising high efficiencies of converting laser light into the desired in-band radiation. Specifically, the tin charge states  $Sn^{10+}-Sn^{14+}$  emit intense in-band radiation. Within these ions, strong dipole transitions from singly excited states closely align around 13.5 nm, caused by strong configuration interaction of the respective atomic sub-shells. Recently, Torretti et al. have found that transitions between multiply excited states in these ions make a prominent contribution to emission features both in and around



Figure 1: Left: Spectral purity of tin plasmas as a function of their optical depth as determined in Chapter 4. The dashed line indicates the SP as expected from a scaling of the spectral emission using an analytical 1D radiation transport model, outlined in Chapters 2 and 4. Right: corresponding spectra for the three wavelength cases depicted in the left panel and normalized to their peak emission. Spectra for 1- and 2- $\mu$ m drive lasers are obtained from irradiating a 30- $\mu$ m-diameter droplet and the spectrum for the 10- $\mu$ m drive-laser case is recorded from a plasma formed from an extended tin target (reproduced from Ref. [13]). The gray shading depicts the in-band region matching the reflectivity of available Mo/Si multilayer optics.

the in-band region [12].

Now, after more than two decades of research and development, tin-dropletbased EUV light sources recently have entered the market and EUV lithography already has become a key technology enabling 7 nm nodes and beyond. Historically,  $CO_2$  gas lasers were chosen to drive the plasma because of good scalability of their output power combined with the high obtainable efficiency of converting laser light into in-band radiation within a  $2\pi$  hemisphere covered by light-collecting optics. This efficiency is referred to as the conversion efficiency (CE). Current machines produce more than 250 W of in-band radiation at CE values of 5-6% [11].

One of the enablers of high CE values using  $CO_2$  lasers is the absorption of the  $\lambda_L = 10.6 \,\mu\text{m}$  laser light in relatively low-density regions of the plasma (typically  $10^{18}-10^{19} \,\text{e}^{-/}\text{cm}^{3}$ ) by the process of inverse bremsstrahlung. A low plasma density is, in turn, typically connected to a high ratio of in-band emission to overall EUV emission. This ratio defines the spectral purity (SP), and SP values as high as 20% have been measured in the case of  $CO_2$ -driven plasmas. An example of the spectral emission of such a  $CO_2$ -driven plasma is shown in Fig. 1. Also shown are spectra for 1- and 2- $\mu$ m wavelength laser irradiation of droplet targets investigated in this thesis. Comparing the three wavelength cases, an advantage of the low den-



Figure 2: CE values simulated using the Lawrence Livermore National Laboratory HYDRA code [14] in one dimension. A thin liquid tin disk is irradiated with a tensof-nanoseconds-long laser pulse of varying laser wavelength ( $\lambda_L$ ) and intensity ( $I_L$ ) to explore CE dependence on these two quantities. Modified from Ref. [15].

sity CO<sub>2</sub>-driven plasma regarding SP becomes apparent in terms of the narrower 13.5 nm emission feature. The broadening of the spectral feature at 13.5 nm in the 1- and 2-µm cases can in part be understood in terms of the higher plasma density at which these shorter drive laser wavelengths are absorbed. Radiation produced in these denser regions, all other things being equal, encounters a higher column density of tin atoms that absorb and re-emit the radiation on its way out of the plasma, re-distributing spectral energy into wavelength bands other than the desired 2% bandwidth around 13.5 nm. The strength of this absorbance and re-emitance is quantified in the optical depth of the plasma. The optical depth is dependent on three factors: first, the ability of the atoms in the plasma to absorb radiation, quantified in terms of the opacity  $\alpha_{\lambda}$ . Second, the length of the emitter column *l*. And third, the density of emitters, expressed in terms of the plasma's mass density  $\rho$ . In case of a short drive laser wavelength, e.g. 1 or 2 µm, the EUV-producing plasma has higher density (compared to a 10 µm CO<sub>2</sub>-driven one), resulting in an increased optical depth that reduces the spectral purity, as shown in the left panel of Fig. 1.

In order to further optimize the CE of EUV light sources, consideration must be given to additional factors, such as the ability of the laser energy to be absorbed by the plasma as well as the fraction of this absorbed energy that is emitted as radiation into the hemisphere covered by light-collecting optics. One such example of this is recent simulation work performed by researchers at Lawrence Livermore

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National Laboratory, shown in Fig. 2. In their simulations, CE was explored regarding the drive laser wavelength as well as its intensity using the HYDRA code [14] in one dimension and laser pulses of several-ten nanoseconds were used to illuminate thin sheets of liquid tin. Interestingly, a significant increase in CE with drive laser wavelength is observed, with a value of  $\sim 3\%$  obtained for a 1-µm driver, ending in a long-stretched optimum of constant CE above 5% starting at just below  $2 \,\mu m$ and continuing to well above 10 µm. This simulation result highlights potentially high-obtainable CE's in the experimentally unexplored near- to mid-infrared region, where efficient high-power, solid-state laser technology has been developed over the last years. A strong advantage of these solid-state laser systems is their up to several times higher wall-plug efficiency than that of  $CO_2$  gas lasers. Especially wavelengths near  $2 \,\mu m$  are of interest where currently very promising high-power Big-Aperture-Thulium (BAT) laser technology at a 1.9-µm wavelength is under development that may become available for EUV light source applications in the near future [16]. Even though the CE for a 1- $\mu$ m drive laser wavelength may be slightly lower, the high wall-plug efficiencies achievable with solid-state laser technology may lead to an overall more efficient EUV light source considering the ratio of usable EUV photons to electrical power. The 1-µm wavelength is further opportune because already today high-power lasers exist at a mature stage of development, ready for industrial use.

Another advantage of a shorter drive laser wavelength is that the higher density of the EUV emitting plasma allows for larger amounts of in-band radiation to be produced within a small plasma volume. This is important as in-band photons are only usable if they are produced within the etendue of the light collecting optics of the light source. The high SP values attainable in  $CO_2$ -driven plasmas come at the cost of emitter density and much larger plasma sizes are required to obtain equivalent amounts of in-band radiation. Consequently, figures of merit next to CE may be needed in the future in the form of, e.g., a CE value normalized to the plasma volume in which the in-band radiation is produced. A final optimization of an EUV light source will need to take into account the amounts of produced debris, be it in the form of fast ionic and atomic debris or larger particles such as tin clusters and microparticles, as well as radiation outside the desired in-band region. This debris needs to be manageable to enable long up-times of the EUV light source.

Because of the complex interplay of all of the above mentioned parameters, a careful optimization of high-power EUV light sources is required for each drive laser wavelength in order to find the optimal operating conditions. Overall, near-infrared solid-state lasers present a very promising class of drive laser candidates for future generations of industrial EUV light sources.

#### Outline and summary

In this thesis, the fundamental limits of converting laser radiation via tin plasma into a 2% bandwidth around 13.5 nm, relevant to nanolithographic applications, are experimentally investigated. For light source optimization, the effects of varying laser irradiation parameters (i.e., laser wavelength, laser intensity and beam spot size) and varying target morphologies on EUV spectra, CE's, SP's and the plasma's optical depth have been studied systematically.

In Chapter 1, the efficiency of radiating EUV light of a spherical tin droplet illuminated by high-energy, 1- $\mu$ m-wavelength laser pulses is investigated. The employed pulses are of constant intensity in space and time to homogeneously heat the plasma. A significant growth of CE and of the overall efficiency in radiating light is found with increasing laser intensity, droplet size and laser pulse duration. The increase in the fraction of laser energy that is radiated away by the plasma is explained by a larger fraction of laser energy absorbed by the plasma, which can be described by a simple plasma expansion model assuming a constant radial plasma expansion speed. By using a more optimal ratio of laser beam to droplet size, promising conversion efficiencies of up to 3.2% are obtained. This 3.2% CE value combined with the higher wall-plug efficiency of 1- $\mu$ m solid-state lasers over CO<sub>2</sub> gas lasers may make 1- $\mu$ m light a feasible drive laser wavelength for EUV light source applications, challenging current industrial sources on their efficiency of converting electrical power to in-band energy.

In Chapter 2, the spectral data of Chapter 1 is analyzed in the context of its optical depth using a one-dimensional, analytical radiation transport model and changes in optical depth with droplet size and laser pulse duration are quantified. The model relates any two experimental spectra, allowing one to reproduce all spectra from any experimental spectrum by means of a single free parameter, the relative optical depth. Using this model, we find a linear increase of optical depth with droplet diameter with a slope coefficient that increases with laser pulse duration. With optical depth being the product of the plasma's opacity, density, and scale length, the increase in optical depth is interpreted as an increase in effective plasma scale length. The results from this chapter provide guidance for EUV light source design, showing that plasma scale length should be kept small to reach the full CE potential in the case of dense,  $1-\mu$ m-driven plasma.

In Chapter 3, a change towards a longer solid-state drive laser wavelength is made, exploring the wavelength regime between the well-known drive-laser cases of 1 and 10  $\mu$ m. Laser pulses of 2- $\mu$ m wavelength, produced by a master oscillator power amplifier system built at ARCNL, are used to create plasma on a planar-solid tin target. The measurements are then compared to ones using a 1- $\mu$ m driver in order to study the change in plasma emission with drive laser wavelength. Via comparison of charge-state-specific features in the recorded emission spectra, we find

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that in order to maintain a certain average charge state in the plasma, and with it the plasma temperature, an inverse linear scaling of drive laser intensity with laser wavelength is required. In the 2- $\mu$ m case, a high CE value of 3.1% is measured at an angle of 60° with respect to the incident laser axis. This value is roughly a factor of 2 higher than the 1- $\mu$ m case under similar experimental conditions. The two times higher CE value correlates well to the observed factor of 2 improvement in SP. In the spectral emission of the 1- $\mu$ m case, strong absorption of in-band radiation is observed which explains the origin of a lower SP value in this case compared to the 2- $\mu$ m case. The absorption of radiation around 13.5 nm is qualitatively explained using an analytical 1D-radiation transport model comprising two plasma zones of different temperature and density, where in Chapter 2 a single zone was sufficient. The high CE and SP for the 2- $\mu$ m driver highlight its potential in driving plasmas in EUV light source applications.

After the brief intermezzo on planar-solid targets, we investigate in Chapter 4 the difference in plasma formation and emission between 1- and 2-µm-driven plasmas from droplet targets. As in Chapter 3, charge-state-specific features between the two wavelength cases are compared, confirming the inverse linear scaling of drive laser intensity with laser wavelength also for the droplet target case. The experimental results are found to be in agreement with theoretical predictions based on the plasma's equation-of-state as well as with results from radiation hydrodynamic simulations conducted with the RALEF 2D code [17]. These simulations reveal an inverse scaling of electron density with laser wavelength. The lower density in the longer drive laser wavelength case is understood from the fraction of laser energy absorbed via inverse bremsstrahlung, which scales with the product of plasma density and drive laser wavelength. Lastly, the recorded spectra are investigated in the context of their peak optical depth, using an improved model from that presented in Chapter 2. A smaller optical depth is found in the 2-µm case and the reduction in optical depth is traced to the reduction in plasma density. The lower optical depth and resulting higher SP values for the 2-µm driver combined with its high coupling efficiency with the plasma again suggest that this wavelength may be well suited for EUV light source applications, allowing for relatively high CE values over a wide range of plasma sizes.

Chapter 5 connects all previous chapters by studying the plasma emission from preformed tin droplets for drive laser wavelengths of 1 and 2  $\mu$ m. In a two-pulse scheme, spherical tin droplets are first deformed to disk-like targets. These disk-like targets are then irradiated using a second, higher-intensity laser pulse. We have studied the influence of target diameter, laser wavelength, laser intensity and laser pulse duration on EUV spectra, SP's and CE's. Surprisingly, high CE values of up to approximately 3% in the 2- $\mu$ m-driven plasma are almost independent of pulse duration and laser intensity within the scanned range. This is a promising result, indicating that EUV light source power may be scaled via those parameters

at little to no cost regarding CE. We further find, as in Chapter 1, that CE is strongly dependent on target size and with it on the fraction of laser energy absorbed by the target, finding back the CE and SP values of the planar-solid and droplet target cases as studied in Chapters 3 and 4. Comparing the two drive laser wavelength cases, we again find strong self-absorption in the 1- $\mu$ m-driven plasma at large target sizes, which drastically reduces the attainable CE's. These results highlight the potential benefits from the use of a 2- $\mu$ m drive laser system in EUV light source applications using mass-limited droplet targets.

In summary, solid-state lasers operating at 1- or 2-µm wavelength show high potential for use as drive lasers in future generations of EUV light sources. In addition to the here conducted studies it is of interest to further extend the range of drive laser wavelengths toward the mid-infrared regime. Even though there are no high-power solid-state lasers readily available in this wavelength range, experimental investigations of plasmas produced at these mid-infrared wavelengths will further deepen the physical understanding of the laser-plasma interaction and measurements of the plasma's spectral emission will aid the understanding of radiation transport processes within the plasma. In addition, further investigations are needed before the possible use of 1- or 2-µm lasers in industrial EUV light sources. First, a more extensive investigation of the obtainable CE using a 2-µm drive laser wavelength is needed. This investigation could include, e.g., heating of the tin targets with a more homogeneous laser intensity profile as was carried out with the  $1-\mu m$  driver in Chapters 1 and 2. Second, it will be of interest to investigate scaling relations that capture the laser pulse parameters required to fully evaporate the tin targets in order to obtain a truly 'mass-limited' EUV light source where no tin particle clusters remain at the end of the EUV-creating laser pulse. For parameter sets where a full evaporation of the target material is achieved, detailed measurements of the size of the in-band emitting region and of the resulting ion debris will be essential to assess the the potential of 1- or 2-µm wavelength drive lasers for use in industrial EUV light sources.

## 1 | Efficient generation of extreme ultraviolet light from Nd:YAG-driven microdroplet-tin plasma

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We experimentally investigate the emission of extreme ultraviolet (EUV) light from a mass-limited laser-produced plasma over a wide parameter range by varying the diameter of the targeted tin microdroplets and the pulse duration and energy of the 1- $\mu$ m-wavelength Nd:YAG drive laser. Combining spectroscopic data with absolute measurements of the emission into the 2% bandwidth around 13.5 nm relevant for nanolithographic applications, the plasma's efficiency in radiating EUV light is quantified. All observed dependencies of this radiative efficiency on the experimental parameters are successfully captured in a geometrical model featuring the plasma absorption length as the primary parameter. It is found that laser intensity is the pertinent parameter setting the plasma temperature and the tin ion charge state distribution when varying laser pulse energy and duration over almost two orders of magnitude. These insights enabled to obtain a record-high 3.2% conversion efficiency of laser light into 13.5 nm radiation and to identify paths towards obtaining even higher efficiencies with 1  $\mu$ m solid-state lasers that may rival those of current state-of-the-art CO<sub>2</sub>-laser-driven sources.

#### 1.1 Introduction

Highly charged tin ions in laser-produced transient plasmas are the atomic sources of extreme ultraviolet (EUV) light at 13.5 nm wavelength for nanolithography [18–32]. In state-of-the-art EUV sources such plasmas are produced by irradiation of micrometer-sized tin droplets with high-power  $CO_2$ -gas-laser pulses [11, 33, 34] in a two-step process where first a laser pre-pulse [11, 33–39] shapes the droplet into a target optimized for EUV production with a second, more energetic pulse. Key physical processes were reviewed by Banine *et al.* [31].

Alternatively, solid-state 1- $\mu$ m-wavelength Nd:YAG laser systems can be used for plasma creation, offering significant advantages over the 10- $\mu$ m-wavelength CO<sub>2</sub> drive laser. The advantages include an improved energy efficiency, a significantly more compact size at same output power and improved temporal pulse shaping capabilities. Moreover they could enable a single-pulse irradiation scheme. YAG systems may in fact replace CO<sub>2</sub> lasers if the efficiency of converting laser energy into radiation within a 2% bandwidth around 13.5 nm that can be reflected by multilayer optics [10, 40] gets sufficiently competitive.

Nd:YAG-driven light sources have a much higher, near complete laser absorptivity due to the strong increase of the critical plasma electron density  $n_c$  with decreasing wavelength  $\lambda$  ( $n_c \propto \lambda^{-2}$ ). The cross section of the here dominant [41] inverse bremsstrahlung absorption mechanism strongly increases with electron density [42, 43]. However, the density increase may cause self-absorption of the emitted EUV light, leading to opacity-broadened emission [44–47]. In turn, more light is emitted outside of the accepted bandwidth. Modeling these opacity effects challenges even the most advanced atomic structure calculations [29] due to the strongly correlated electronic structure of the multielectron open-4*d*-shell tin ions raising the need for experimental investigations.

The literature on Nd:YAG-driven tin plasma mostly deals with the emission from planar-solid targets [46–57], tin-coated spherical targets [44, 58–62], or liquid-droplet targets out of tin alloys [63]. The literature covering the emission properties of laser-produced plasma (LPP) from high-purity tin microdroplets, the industrial targets of choice, remains scarce [64–66].

Here, we present the results of a systematic investigation of the characteristics of the EUV spectra of these sources over a wide parameter range, varying the diameter of the targeted, pure tin microdroplets (16–65  $\mu$ m), the laser pulse duration (0.5–25 ns) and its energy, presented as intensity [(0.1–2.7) × 10<sup>11</sup> W/cm<sup>2</sup>], using a transmission-grating spectrometer [67, 68]. The combination of this spectroscopic data with absolute measurements of the *in-band* emission in the 2% bandwidth around 13.5 nm enables three linked figures of merit to be obtained characterizing the emission from the plasma: spectral purity, conversion efficiency, and radiative efficiency. Conversion efficiency (CE) is commonly used and represents

the ratio of  $E_{\text{IB},2\pi}$  over the energy of the drive laser  $(E_{\text{L}})$ .  $E_{\text{IB},2\pi}$  is the total in-band radiation emitted into the half sphere back towards the laser that is reflected by the light collection optics in industrial sources. Spectral purity (SP) is defined as the ratio of  $E_{\text{IB},2\pi}$  and total EUV energy  $(E_{\text{rad},2\pi})$  emitted in the same half sphere. Through basic energy conservation considerations, SP serves as an absolute upper limit to the conversion efficiency: CE  $\leq$  SP, where CE approaches SP only in the case of light emission solely in the backward-facing half sphere. This limit value is lowered by considering that light is also emitted in the opposite, forward-facing half sphere. Indeed, a more stringent limit of CE  $\leq$  SP/2 holds in the case of spherically symmetric emission [69]. These limits emphasize the importance of spectroscopic investigations as introduced here.

Considering the application purposes, the radiative efficiency  $\eta_{\rm rad}$  is defined as the ratio of  $E_{\rm rad,2\pi}$  to laser energy  $E_{\rm L}$  and it thus equals the ratio CE/SP. Simulation works predict that in total 70% up to 90% of the absorbed laser light is emitted as radiation [70–72]. For optimal, high-CE source operation both SP and radiative efficiency should be as high as possible. A further crucial requirement is that the plasma should create manageable amounts of debris comprising, e.g., fragments or high-energy particles that could limit the optics lifetime. Laser energy not contributing to radiation may instead contribute to generating fast ionic debris. Possible gains in radiative output power should be carefully measured out against, e.g., increases in the material load on the optical components. A full quantification of various debris loads is left for future work.

In order to optimize the three figures of merit of EUV-source operation, we introduce a geometrical model with the plasma-absorption length as its prime parameter. The model describes very well the dependencies of  $\eta_{rad}$  on source parameters such as droplet size and laser-beam size. Employing these insights, we obtain a record-high CE of 3.2% and identify paths towards even higher values.

This paper is structured as follows. In Section 1.2 the experimental setup is introduced, followed by a description of the measurements in Section 1.3. A plasma expansion model is presented in Section 1.4 that is applied to the experimental data in Section 1.5. In Section 1.6 we apply the found scalings to an industrially relevant case and close with a discussion of our findings in Section 1.7.

#### **1.2** Experimental setup

Molten Sn of 99.995% purity is pushed through a capillary glass tube with a micrometer-sized orifice into a vacuum chamber of  $5 \times 10^{-7}$  mbar background pressure. Plateau-Rayleigh instabilities lead to the breakup of the liquid stream into small fragment droplets. Evenly sized microdroplets are produced from these fragments by inducing a pressure modulation on the liquid stream in the glass tube leading to a



Figure 1.1: Schematic representation of the experimental setup. The laser beam, depicted in red, illuminates the falling tin microdroplets (gray spheres). The produced plasma emission is observed using a transmission-grating spectrometer (gray box) as well as four EUV photodiode assemblies (gray cylinders) measuring the absolute amount of produced in-band radiation. All angles  $\theta$  are indicated with respect to the laser-beam propagation axis, with  $\cos \theta = \cos \phi \cos \varphi$ .

controlled coalescence of the smaller fragment droplets. The resulting microdroplet size, measured using imaging techniques [35, 70], is controlled by variation of the applied modulation frequency. Modulation frequencies between 3 and 100 kHz are used resulting in droplets between 65 and 20  $\mu$ m in diameter. Above 100 kHz the interdroplet spacing is on the order of the laser-beam spot size; therefore, in order to produce droplets as small as 16  $\mu$ m with sufficient spacing, we make use of imperfect coalescence resulting in periodic groups of smaller and bigger droplets.

The droplets travel at 10 m/s through a He-Ne laser light sheet scattering the laser light, which is subsequently detected by a photomultiplier tube and used to trigger the drive laser and the data-acquisition system at 10 Hz. After detection, the droplet is irradiated by a linearly polarized, high-intensity laser pulse from an in-house built Nd:YAG laser system seeded at 1064 nm [73]. The laser system produces a flat-top spatial profile and has temporal pulse-shaping capabilities allowing the production of pulses from 0.4–1000 ns duration. All but the 0.5-ns pulse are box-shaped and their duration is measured as FWHM.

With the purpose of maintaining the homogeneous spatial intensity distribution, the laser beam is imaged from the exit of the amplifier rod onto the droplet. In order

to match droplet and laser-beam spot size, and to reach the necessary intensities on the order of  $10^{11}$  W/cm<sup>2</sup>, the laser beam is demagnified to 96 µm FWHM. Of the total laser pulse energy, a fraction of 80% falls within the FWHM area. To obtain an even smaller beam spot size of 56 µm, used for measurements described in Section 1.6, a 3.5-mm aperture is placed in the object plane of the beam. In both cases, the laser-beam spot is slightly elliptical, with less than 25% difference between the major and minor axis, and we use the average value of the two axes. The laser-beam energy is controlled using a combination of a half-wave plate and a thin-film polarizer without affecting the spatial intensity distribution.

The spectral emission of the produced plasma is observed under an angle of  $60^{\circ}$  (see Fig. 1.1) using a broadband transmission-grating spectrometer [67, 68]. The spectrometer is operated with an entrance-slit width of 25 µm and a 10 000 lines/mm grating obtaining an instrument resolution of 0.1 nm FWHM at 13 nm [67]. The dispersed light is captured by a back-illuminated CCD from Greateyes (GE2048 512BI UV1), cooled to  $-30^{\circ}$ C to reduce thermal noise.

The measured images are cropped and corrected for shear and tilt introduced by a slight misalignment of slit and grating with respect to the camera pixel array. Afterwards the images are averaged over the non-dispersive axes and the read-out noise and dark counts are eliminated by subtracting a dark exposure image (i.e., an image obtained using the same exposure time but without plasma present). Calibration of the dispersive axis is performed using reference spectra entailing tabulated [74], well-known Al<sup>3+</sup> and Al<sup>4+</sup> line features between 11 and 16 nm. The calibration spectra are taken after the experiments by irradiating a solid aluminum target with the Nd:YAG laser at the same position as the droplets. After calibration, the spectra are corrected for second-order contributions in the wavelength range above 11 nm using the second-order diffraction efficiency of the grating [68]. Lastly, the spectra are divided by the first-order diffraction efficiency of the grating as well as the quantum efficiency of the camera. Since the grating transmission is not calibrated below 5.5 nm, all SP values in the following are calculated for a wavelength range of 5.5-25.5 nm. Given the low emission anisotropies observed over the backward half sphere (see below), spectra obtained under an angle of 60° are used for SP.

To obtain an absolute measurement of the produced in-band radiation (13.5 nm  $\pm 1\%$ ), four silicon photodiode assemblies are mounted under angles of 30°, 42°, 64° and 90° (Fig. 1.1). Photodiode measurements are corrected for their respective solid-angle coverage. These assemblies use Mo/Si multilayer mirrors (MLMs) [10, 40] as found in industrial sources to reflect the in-band part of the radiation onto the photodiodes. Any remaining optical light reflected by the MLMs is subsequently removed by a Si/Zr coating on the photodiodes (SXUV100), which is transmissive for in-band radiation. The response function of all individual components is known, providing a measure of the absolute amount of produced in-band radiation.



Figure 1.2: Angular dependency ( $\theta$ ) of the in-band emission with respect to the laserbeam axis. Depicted are measurements for the 96-µm laser-beam size. For each pulse duration, the data from the smallest and biggest droplet sizes are shown normalized to their maximum values. The dashed blue line is the result of a global fit of Eq. (1.2).

In order to take into account the emission anisotropy over the backward half sphere where CE is defined, we integrate the angular dependency  $f(\theta)$  of the inband emission. For integration the obtained measurements from the photodiodes in Fig. 1.2 are used, employing the cylindrical symmetry of the system with respect to the laser beam axis

$$CE \propto \int_{0}^{\pi/2} d\theta f(\theta) \sin(\theta),$$
 (1.1)

where the angular dependence  $f(\theta)$  of the in-band emission is typically described by (e.g., Refs. [52] and [75])

$$f(\theta) = \alpha + \beta \cos^{\gamma}(\theta). \tag{1.2}$$

Fitting Eq. (1.2) to the measured data, we obtain the following values for the fit parameters:  $\alpha = 0.82(2)$ ,  $\beta = 0.17(3)$ , and  $\gamma = 0.6(3)$ . From integration we obtain a value for the anisotropy-corrected CE that is only 5% lower than the value from the photodiode under 30° angle that we use throughout this paper, extrapolated assuming isotropic emission.

#### 1.3 Measurement results

In order to optimize SP and  $\eta_{rad}$ , and therewith CE, we vary three key parameters of our LPP source: laser intensity (see Fig. 1.3), laser pulse duration and droplet size. Following this order, we describe below their impact on the observed spectra and the values of SP and CE as presented in Fig. 1.4. The trends in the radiative efficiency, defined as  $\eta_{rad} \equiv$  CE/SP are described in Section 1.5. It is preceded by the introduction of a plasma expansion model in Section 1.4 describing the scaling of  $\eta_{rad}$ .

#### Laser intensity

We start by describing the effect of changing the laser intensity using the example of a 96-µm-sized, 15-ns-long laser-beam pulse and a 46-µm-diameter droplet. The intensity, calculated as  $I = E_{\rm L}/(\tau \pi w^2)$  using the laser pulse duration  $\tau$  and laser-beam radius w = FWHM/2, is varied over more than 1 order of magnitude in the range of  $(0.1-2.7) \times 10^{11} \text{ W/cm}^2$  by changing the laser-beam energy. The normalized emission spectra arising from these experimental conditions are shown in Fig. 1.3 and in reduced size in Fig. 1.4(a).

The most prominent characteristic observed in Fig. 1.3 is the shift of the main emission feature from 15 nm toward the desired 13.5 nm with increasing laser intensity. This shift is related to the creation of tin ions of higher charge states  $(Sn^{8+}-Sn^{15+})$  relevant for in-band emission [18, 21, 23, 29]. Additionally, the main emission feature narrows towards higher intensity, reaching a FWHM of 0.9 nm at  $1.4 \times 10^{11}$  W/cm<sup>2</sup>.

To resolve which charge states are contributing to in-band emission at a given intensity we look at the short-wavelength emission between 7 and 12 nm. As described in Refs. [20] and [76],  $\text{Sn}^{8+}-\text{Sn}^{15+}$  have unique emission features in this regime stemming from radiative decay out of electronic configurations such as, e.g., the  $4p^5 5s$  in  $\text{Sn}^{14+}$  where a 4p core electron is promoted to the 5s subshell. These configuration lie above the in-band contributing  $4p^5 4d^{m+1} + 4p^6 4d^{m-1} 4f + 4p^6 4d^{m-1} 5p$  (cf. Fig. 1.3). Using such out-of-band features as diagnostics it is evident that for the highest laser intensity ( $2.7 \times 10^{11} \text{ W/cm}^2$ ) charge states of at least up to  $\text{Sn}^{15+}$  are present in the plasma.

The above observations relate to the trend in SP values presented in Fig. 1.4(d) where we see a sharp increase in SP between 0.1 and  $0.5 \times 10^{11}$  W/cm<sup>2</sup>. Above  $0.5 \times 10^{11}$  W/cm<sup>2</sup> the incline in SP slows down and SP levels off in the range of  $(0.8-1.7) \times 10^{11}$  W/cm<sup>2</sup> before it decreases again. The sharp increase in SP is explained by an increase in average charge state of the plasma causing reduced emission above 16 nm while favoring in-band emission. At the same time the amount of short wavelength radiation (below 12 nm) increases steadily. Nevertheless, SP con-





tinues rising due to the narrowing of the main spectral feature at 13.5 nm. Above  $1.4 \times 10^{11} \text{ W/cm}^2$  SP declines very slowly because the main emission peak stops narrowing while the amount of short wavelength radiation keeps on increasing. At intensities above  $1.7 \times 10^{11} \text{ W/cm}^2$  the main feature widens again leading to a more rapid decrease of SP. For the lowest and highest intensities measured an increasing fraction of the emission is outside the measured or calibrated range, respectively, slightly increasing the SP.

Even though SP decreases again at higher intensities, CE monotonically increases over the entire intensity range as shown in Fig. 1.4(d), reaching values up to 1.9%.

#### Laser pulse duration

In this section we explore the influence of laser pulse duration on the plasma emission as presented in Fig. 1.4(b). For the measurements we chose an intensity of  $1.4 \times 10^{11}$  W/cm<sup>2</sup> at which the main emission feature is narrowest and SP is highest. The droplet diameter as well as the beam size are left unchanged at 46 and 96 µm, respectively.

Upon reducing the laser pulse duration, a narrowing of the main emission peak at 13.5 nm is visible as well as a reduction of the short and long wavelength radiation. The only exception is the pulse duration of 0.5 ns for which the main feature widens again and more emission is observed above 16 nm. For all pulse durations the strong resemblance of the spectra is remarkable indicating that the laser intensity is the pertinent parameter setting the plasma temperature and charge-state distribution. All spectra show similar features and only small differences are visible in the relative emission intensity around 8 nm as well as in the width of the dominant feature at 13.5 nm. The widening of the main emission feature can be attributed to changes in optical depth of the plasma induced by the different plasma sizes for the various laser pulse durations. The larger optical depth causes increased absorption and re-emission of EUV radiation resulting in the observed broadening of the spectral features.

Translating these observations into the SP curve in Fig. 1.4(e), we see an increase in SP from 0.5 to 2.5 ns where it reaches its maximum value. Above 2.5 ns a steady but rather weak decrease from 12% to 8% is visible.

As in the preceding subsection, the measured CE monotonically increases with pulse duration. In the scanned parameter range a relatively high CE of 2.2% is reached at 25 ns.



Figure 1.4: (Figure on previous page) Top row: spectra for tin microdroplets irradiated by (a) various Nd:YAG laser pulse intensities, (b) laser pulse durations, and (c) droplet sizes. The gray vertical bar depicts a 2% bandwidth around 13.5 nm. Center row: SPs (here divided by a factor 2 for convenience) and CE corresponding to the spectra above. Bottom row: radiative efficiencies ( $\eta_{rad} \equiv CE/SP$ ) and the result of a global fit of our plasma expansion model as described in Section 1.5 (solid lines). The gray dashed lines in (g)–(i) depict the geometrical overlap  $(R_0^2/2w^2)$  of laser beam and droplet for isotropic emission.

#### **Droplet size**

Lastly, we show the effect of a change in droplet diameter onto the spectral emission in Fig. 1.4(c). For the measurements shown a pulse duration of 15 ns was used at an intensity of  $1.4 \times 10^{11}$  W/cm<sup>2</sup>. Enlarging the droplet diameter leads to increased relative emission at wavelengths below 13 nm while all spectra show strong similarity with respect to their emission features. Again, predominantly the width of the main emission feature varies and its change can be attributed to changes in the optical depth of the plasma.

Looking at SP in Fig. 1.4(f), we find a steady decline from 13% at 16  $\mu$ m to 8% at 58  $\mu$ m diameter. Once more, in contrast to the scaling of SP, CE monotonically increases over the entire range of droplet diameters.

#### 1.4 Plasma expansion model

For all cases presented in Fig. 1.4, CE increases monotonically with the scanned parameter, even when SP declines. This behavior can be understood as an increase in radiative efficiency that counteracts the losses in SP for bigger droplets and longer pulses. To describe the changes in radiative efficiency with respect to laser intensity, pulse duration, and droplet radius we develop a model taking into account the increase in laser light absorption due to plasma expansion during the laser irradiation.

In the model,  $\eta_{rad}$  is proportional to the absorbed laser light assuming that a constant fraction is lost to plasma kinetics. At time  $t_0$  when the laser pulse arrives at the droplet the absorbed laser light fraction equals the spatial overlap of droplet and laser beam. At the intensities used, reflectivity can be neglected, resulting in full absorption within the overlap region [70].

The absorbed laser light leads to ablation and plasma creation beyond a certain threshold laser intensity [35, 70]. This plasma expands establishing a radial density gradient around the droplet [70] (see Fig. 1.5). All laser light is absorbed close to an electron density that is of the order of, but below, the critical electron density



Figure 1.5: Schematic representation of the laser-produced plasma system. The laser pulse (orange shaded area) propagating in positive *z* direction is absorbed by the liquid Sn droplet of radius  $R_0$  (gray sphere). During laser irradiation plasma is created around the droplet (light gray shaded area) increasing the absorbing area. The latter expands with a constant velocity v laterally to the laser-beam propagation direction, increasing the effective radius of absorption to  $R_{\text{eff}} = R_0 + vt$ .

for the Nd:YAG laser wavelength  $(n_c = 1 \times 10^{21} \text{ e}^-/\text{cm}^3)$  [41]. With time, the density contour at which laser light is absorbed moves outwards and the absorptive area increases. Analogously to Refs. [35] and [77], we introduce a power law, here for the lateral expansion speed  $v(I) = a \times I^b$ , at which this density contour moves outwards. The expansion speed is constant over the duration of the laser pulse. Before the plasma can efficiently emit radiation it needs to be heated to reach the relevant plasma temperatures. During this time no significant amount of in-band radiation is emitted implying a lowering of the radiative efficiency. To capture this effect a plasma heat-up time  $t_h$  is introduced as a multiplicative factor  $(1 - t_h/\tau)$  following Ref. [78], where  $\tau$  is the laser pulse duration. To account for the fraction of laser energy lost to plasma kinetics and into radiative efficiency  $\eta_{\text{max}}$ .

Next, we divide the calculation into three cases: (i)  $R_0 + v\tau \le w$ ; (ii)  $R_0 + v\tau > w$ ; (iii)  $R_0 \ge w$ . In case (i), the droplet is initially smaller than the beam and the absorbing area expands during the laser irradiation, but will not exceed the laser-beam size during the pulse. In case (ii), the droplet is smaller than the beam but the absorbing surface exceeds the laser-beam size before the laser pulse ends. In this case we neglect any expansion beyond time  $t_w = (w - R_0)/v$  when the absorbing surface exceeds the laser beam because from thereon full overlap of laser and plasma is reached. In the most extreme case (iii), the liquid droplet

itself is already larger than the beam leading to unity absorption during the entire laser pulse duration. These considerations lead to the following smooth, continuous global fit function:

$$\eta_{\rm rad} = \left(1 - \frac{t_h}{\tau}\right) \eta_{\rm max} \times$$
(1.3)  
$$\begin{cases} \frac{\frac{1}{3}v^2 \tau^3 + R_0 v \tau^2 + R_0^2 \tau}{w^2 \tau} & \text{(i)} \\ \frac{\frac{1}{3}v^2 t_w^3 + R_0 v t_w^2 + R_0^2 t_w}{w^2 \tau} + \frac{\tau - t_w}{\tau} & \text{(ii)} \\ 1 & \text{(iii)} \end{cases}$$

There are only three main free fit parameters, being  $\eta_{\text{max}}$ ,  $t_h$ , and  $\nu$ , where the latter is, in turn composed of two free fit parameters *a* and *b* (relevant only for the laser-intensity dependency).

#### 1.5 Model fit and discussion

The obtained radiative efficiencies are presented in Fig. 1.4(g)–1.4(i) and our model can be used to understand the monotonous nature of their rise with all varied parameters. The result of a single, *global* fit of our model (see Eq. (1.3)) to all experimental data related to the variation of the laser pulse duration and droplet diameter is depicted in Fig. 1.4(h) and 1.4(i), where all data is taken at a constant intensity of  $1.4 \times 10^{11}$  W/cm<sup>2</sup>. An excellent agreement between model and experiment is obtained. From the fit a plasma expansion velocity  $v = 0.9(1) \,\mu$ m/ns, a maximal radiative efficiency of  $\eta_{\text{max}} = 49(2)\%$  and a plasma heat-up time  $t_h = 0.34(2)$  ns are retrieved. The radiative efficiency from the geometrical laser-droplet overlap, without considering the expanding plasma, is given by  $R_0^2/2w^2$  for isotropic emission shown as dashed lines in Fig. 1.4(g)–1.4(i).

The plasma heat-up time  $t_h$  agrees well with the 0.4 ns calculated in Ref. [79] for Nd:YAG-produced Sn plasmas of about 30-eV temperature. However, further transient effects in the plasma due to, e.g., the finite rise and fall times that are a dominant part of the shortest pulse, cannot be excluded. Given its small, sub-ns value,  $t_h$  has negligible impact on radiative efficiency except for the shortest, 0.5-ns pulse-duration case.

The fitted value of the maximal radiative efficiency of 49% (with a highest experimentally obtained value of approximately 35%) comes close to the maximally possible value of 50% in the case of isotropic emission. As energy is invariably lost through other processes such as ionization and plasma kinetics, we conclude that a finite anisotropy conveniently causes a preferred emission of light into the backwards half sphere as also indicated, e.g., in Ref. [66].

O'Shay *et al.* [71] estimated the total amount of radiated energy from a tin LPP in  $4\pi$  steradian to be on the order of 90% of the absorbed laser energy. Tillack *et al.* [72] simulated the energy balance of spherical tin targets and concluded that about 70% of the energy is converted into radiation. This is in broad agreement with the 70–80% estimate from the simulations presented in Ref. [70]. Combining our fit value with this approximately 80% theory value we conclude that approximately 30% of the laser light is converted into radiation emitted in the forward half sphere. The in-band emission anisotropy in Fig. 1.2 also evidences a slight preference for backward emission. These findings are further supported by Refs. [64] and [65]. Our CE results are consistent with those obtained in Ref. [64] taking into account the droplet and beam spot sizes used.

The expansion velocity obtained from the fit agrees well with those inferred from radiation hydrodynamic simulations [70]. In that work, a 46-µm-diameter droplet was irradiated by a 115-µm FHWM Gaussian Nd:YAG laser beam at an average intensity of  $1.3 \times 10^{11}$  W/cm<sup>2</sup>. A dominant, 80% fraction of the laser light is absorbed in the region close to but before the critical surface [41]. Lateral expansion speeds on the order of  $v \sim 1 \,\mu$ m/ns resulted from the simulations for densities approximately (0.1–0.5) $n_c$ .

Using the global fit values for  $\eta_{\text{max}}$  and  $t_h$ , we next apply and fit our model to the laser-intensity dependency in Fig. 1.4(g). Again, an excellent agreement is found between model and experiment, obtaining the parameter values a = 0.69(5) and b = 0.8(1). This near-linear dependence of v on I is in line with the simulation data underpinning Ref. [70]. We note that  $t_h$  may also depend on intensity but its contribution to the 15-ns pulse-duration case is marginal and completely removing  $t_h$  from Eq. (1.3), in fact, does not significantly change the obtained values for the expansion velocity parameters a, b.

In conclusion, we can describe the scaling of the radiative efficiency with all studied parameters by a model describing the increase of laser absorption with plasma expansion. Excellent overall agreement between model and experimental data is obtained. We note that in our current investigations the effective radius  $R_{\text{eff}} = R_0 + v\tau$  remained below the beam radius *w* corresponding to case (i) in Eq. (1.3). The finite ellipticity of the laser-beam spot is not expected to significantly influence the measurements as the plasma expansion does neither exceed minor nor major axis. Values above our experimental maximum of 35%, possibly nearing 50%, appear to be feasible. Thus, in order to obtain high CE, a set of parameters needs to be found where a high value for SP is achieved while optimizing the absorbed fraction of laser light, or radiative efficiency. Changing the beam size in the following section enables us to probe beyond model case (i) and maximize radiative efficiency.

#### 1.6 Increasing radiative efficiency

In order to increase the radiative efficiency, and with it CE, the laser-beam size is reduced to 56  $\mu$ m. As before, the beam-to-droplet overlap is scanned by changing droplet size (Fig. 1.6). The laser intensity is set to an optimal  $1.4 \times 10^{11}$  W/cm<sup>2</sup> for SP and the laser pulse duration to 15 ns. The spectra for the small beam spot size in Fig. 1.6(a) show a small but significant broadening of the main emission feature on its long wavelength side with a corresponding systematic reduction of SP in Fig. 1.6(b). This may be related to an absence of heating of the outer plasma layers beyond 56  $\mu$ m.

A considerable overall increase in CE is obtained for all droplet sizes. It monotonically rises with the droplet diameter reaching a record-high value of 3.2%. We note that the ever more slowly decreasing values for SP/2 and increasing CE appear to converge to a common value. This intriguing observation indicates that the limit CE  $\leq$  SP/2, strictly valid only for isotropic emission [69], may provide a good estimate for the maximally reachable CE value of the plasma source.

Over the entire range measured, the radiative efficiency is monotonically increasing and significantly higher than for the 96- $\mu$ m laser beam (see Fig. 1.6(c)). Comparing the small-beam measurements to the model results of Section 1.5, we plot Eq. (1.3) using the values for v and  $t_h$  as determined from the global fit in Fig. 1.4. We set the beam spot size to 56  $\mu$ m leaving only  $\eta_{rad}$  as a free fit parameter. The model fit shown with the dashed-dotted line in Fig. 1.6(c) is in excellent agreement with the experimental data. The obtained value for  $\eta_{max} = 42(1)\%$  is slightly lower than before, although within systematic uncertainties of determining beam spot and droplet size. The regime probed by these small-beam measurement includes model cases (ii) and (iii) that are not reachable in Section 1.5. In these cases, the laser beam does not directly heat the laterally expanding high-density plasma at radii  $R_{\text{eff}} > w$ , which may affect  $\eta_{\text{rad}}$  through differences in the energy partitioning between forward and backward emission, and plasma kinetics. Further, the finite ellipticity of the laser-beam spot may slightly influence the measurements as the plasma expansion in these cases (ii) and (iii) exceeds major and minor axis over the scanned parameter range.

Aside from the already explored reduction of laser beam-spot and increase of droplet size to improve  $\eta_{rad}$ , our model shows that laser pulses of even longer duration could also be employed to compensate for a geometrical mismatch. For all three solutions, increases in  $\eta_{rad}$  are partially offset by a decrease in SP. Given the limit conditions CE  $\leq$  SP or the apt CE  $\leq$  SP/2, any global approach to source optimization needs to maximize both SP and the laser-plasma overlap captured by  $\eta_{rad}$ . Based on these considerations and our spectroscopic measurements in Fig. 1.6(a) from which we obtain values for SP above 12%, conversion efficiencies of CE = SP/2 = 6% may in fact be achievable. These values would rival those of cur-



Figure 1.6: (a) Spectra for two droplet sizes and two laser-beam sizes (see main text) at a laser intensity of  $1.4 \times 10^{11}$  W/cm<sup>2</sup>; (b) values for SP/2 and CE versus droplet diameter for the two laser-beam sizes; (c) radiative efficiency versus droplet diameter for the two laser-beam sizes. The dash-dotted and solid lines represent the model curves. For the 56-µm laser beam, the regimes corresponding to the three model cases (i)–(iii) of Eq. (1.3) are highlighted by the vertical dashed lines (see main text).

rent CO<sub>2</sub>-laser-driven sources. To obtain such efficiencies, the observed systematic decrease of SP with decreasing beam size needs to be negated. The model points towards another class of solutions including maximizing  $\eta_{rad}$  by using a separate laser 'pre-pulse' to predeform the microdoplet into a disk shape [11, 33–39] that closely matches the applied 'main' laser beam-spot size.

#### 1.7 Conclusion

We experimentally investigate the emission of EUV light from Nd:YAG laser-produced plasma over a wide parameter range, varying the laser energy, its pulse duration, and the size of the tin microdroplets. Spectroscopic measurements combined with absolute measurements of the emission into a 2% bandwidth around 13.5 nm allow us to obtain the scaling of three coupled parameters: the spectral purity SP, the conversion efficiency CE, and the radiative efficiency  $\eta_{\rm rad}$  expressed as the ratio CE/SP. We successfully capture all observed scalings of  $\eta_{rad}$  in a geometrical model featuring the plasma absorption length as the pertinent parameter. Using a smaller laser-beam spot size, approaching the size of the droplets, we obtain a record-high 3.2% conversion efficiency of laser light into in-band radiation. Energy conservation considerations bind the maximum value of CE to SP/2 for isotropic emission, and our measurements strongly hint at the convergence of CE towards this theoretical limit. A 6% conversion efficiency value may thus be achievable in future experiments that should also quantify and compare the debris produced by Nd:YAG laser-produced plasma sources to industrial ones using CO<sub>2</sub> lasers. High values for the key parameter, the conversion efficiency, are indeed obtainable from a single 1-µm-laser-pulse irradiation scheme. Combining these high conversion efficiency values with the advantages of reduced footprint, beneficial wall-plug efficiency, and laser stability this work enhances the prospects that Nd:YAG-driven LPP light sources will find application in EUV nanolithography.
## 2 | Radiation transport and scaling of optical depth in Nd:YAG laser-produced microdroplet-tin plasma

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Experimental scaling relations of optical depth are presented for the emission spectra of a tin-droplet-based, 1-µm-laser-produced plasma source of extreme ultraviolet (EUV) light. The observed changes in the complex spectral emission of the plasma over a wide range of droplet diameters (16-65 µm) and laser pulse durations (5-25 ns) are accurately captured in a scaling relation featuring the optical depth of the plasma as a single, pertinent parameter. The scans were performed at a constant laser intensity of  $1.4 \times 10^{11}$  W/cm<sup>2</sup>, which maximizes the emission in a 2% bandwidth around 13.5 nm relative to the total spectral energy, the bandwidth relevant for industrial EUV lithography. Using a one-dimensional radiation transport model, the relative optical depth of the plasma is found to linearly increase with droplet size with a slope that increases with the laser pulse duration. For small droplets and short laser pulses, the fraction of light emitted in the 2% bandwidth around 13.5 nm relative to the total spectral energy is shown to reach high values of more than 14% which may enable conversion efficiencies of Nd:YAG laser light into-industrially-useful EUV radiation rivalling those of current state-of-the-art CO<sub>2</sub>-laser-driven sources.

#### 2.1 Introduction

The semiconductor industry is currently moving from deep-ultraviolet to extreme ultraviolet (EUV) lithography for high-volume manufacturing of the next generation of microelectronics where the shorter wavelength of the EUV radiation enables further miniaturization. The light sources of choice for the nanolithographic applications are laser-produced plasmas (LPPs) [11, 18–32, 80–82]. In these sources, tens-of-micrometer-sized tin droplets are irradiated by high-intensity ( $10^{10}$  W/cm<sup>2</sup>) laser pulses, in order to generate a high-density ( $10^{19}$  e<sup>-</sup>/cm<sup>3</sup>) plasma that efficiently emits EUV radiation [83]. Tin is used because several of its charge states have strong dipole transitions such as the 4d-4f, 4p-4d, and 4d-5p arrays in Sn<sup>8+</sup>–Sn<sup>15+</sup> which strongly emit around 13.5 nm [18, 27], a wavelength that matches the peak reflectivity of available Mo/Si multilayer optics [10, 40] used in state-of-the-art EUV-lithography. The light of interest within a 2% bandwidth around 13.5 nm is referred to as *in-band* radiation.

Currently,  $CO_2$ -gas lasers operating at 10  $\mu$ m wavelength are used to drive the EUV-emitting plasma, but with further developments regarding their output power, YAG solid-state lasers operating at 1  $\mu$ m may become a viable alternative in the future. YAG laser systems provide a smaller footprint, a significantly higher efficiency in converting electrical power to laser light, and excellent temporal pulse shaping capabilities. The shorter 1 µm wavelength of YAG lasers gives rise to a 100 times higher critical plasma density  $(n_{\rm crit} \propto \lambda^{-2})$  compared to CO<sub>2</sub>-laser-driven plasmas, and higher laser intensities of typically  $10^{11}$  W/cm<sup>2</sup> are needed to efficiently produce in-band radiation. The higher critical density results in a much higher, nearly complete absorption of the laser light by the tin target through the mechanism of inverse bremsstrahlung [42, 69]. A possible adverse effect of the higher critical plasma density is the creation of EUV radiation in plasma regions of higher density and high opacity. Significant self-absorption of the emitted radiation can lead to a broadening of the spectral emission out of the 2% bandwidth of interest, thus reducing the spectral purity (SP) of the EUV plasma source [44-47]. SP is defined as the ratio of in-band energy ( $E_{IB,2\pi}$ ) over the total EUV energy ( $E_{rad,2\pi}$ ) emitted into the hemisphere back toward the laser that is covered by multilayer optics in industrial sources. Conversion efficiency CE is defined as the ratio of the total produced in-band energy  $E_{\text{rad},2\pi}$  and the total incident laser energy. Considering conservation of energy, SP represents the absolute upper limit to the conversion efficiency:  $CE \leq SP$ , where CE approaches SP only if all light is emitted in the backward-facing  $2\pi$  steradian and no laser energy is converted into other energy channels such as kinetic energy of charged particles [84]. A more stringent limit of  $CE \leq SP/2$  is found in the case of spherically symmetric emission [69]. Given the importance of SP as indicator for source performance, its scaling with relevant source parameters such as tin-droplet size, laser pulse duration and laser beam spot size needs to be

quantified and understood. The existing literature on Nd:YAG-laser-driven plasma from high-purity tin microdroplets [64–66], the industrial targets of choice, mainly focuses on the integrated amount of produced in-band emission rather than on the spectral properties of the plasma, despite the importance of SP.

In this Letter, a systematic study of the influence of droplet size and laser pulse duration on the emission spectrum of a droplet-based, Nd:YAG-driven EUV source is presented. An analytical solution for radiation transport in an optically thick onedimensional plasma is used to quantify opacity driven broadening of key emission features.

## 2.2 Experiment

In the experiment, spherical micrometer-sized liquid tin droplets were irradiated with high-intensity laser pulses from a Nd:YAG laser system[73] operated at 1064 nm as described in Ref. [35] and [84]. The laser pulse was temporally box shaped and of adjustable duration. It had a spatially flat-top shape of 96  $\mu$ m diameter to homogeneously heat the plasma. The spectral emission from the plasma was observed with a transmission grating spectrometer [68] under 60° with respect to the incoming laser beam. The measured spectra were corrected for the grating's first and second order diffraction efficiency as well as for the quantum efficiency of the camera. After correction, the SP values were calculated with respect to the measured spectral range of 5.5–25.5 nm. The wavelength was calibrated in a separate experiment using atomic line emission from an aluminum plasma. Using a laser intensity of  $1.4 \times 10^{11}$  W/cm<sup>2</sup> at which SP is optimal [84], two sets of experiments were conducted.

First, spectra were measured for several laser pulse durations within the range of 5-25 ns while keeping the droplet size fixed at  $46 \,\mu$ m. As seen in Fig. 2.1(a), the main emission feature at 13.5 nm broadens for longer laser pulse duration, while all other spectral emission features stay remarkably similar even though the laser pulse duration was varied by a factor of five. This indicates that laser intensity is the pertinent parameter of the investigated LPP determining charge state distribution and temperature of the plasma [84, 85].

Second, spectra were measured for various droplet sizes in the range of 16– 65  $\mu$ m at constant laser pulse durations of 5, 15 and 25 ns. Spectra for the 15-ns case are shown in Fig. 2.1(b). A striking similarity in spectral structure is observed among plasmas formed on droplets of various sizes. With increasing droplet size, the main spectral feature at 13.5 nm broadens and the short-wavelength radiation between 5.5 and 12 nm increases in intensity relative to the main emission feature.



Figure 2.1: Selection of emission spectra of Nd:YAG-laser-produced plasma from tin microdroplets irradiated at a constant laser intensity of  $I = 1.4 \times 10^{11} \text{ W/cm}^2$  while varying either (a) the laser pulse duration or (b) the droplet diameter.

## 2.3 Methods

The observed broadening of spectral features for increased pulse duration and droplet size, illustrated in Fig. 2.1, can be connected to an increase in the optical depth of the emitting plasma. The spectral radiance  $L_{\lambda}$  of a plasma with significant absorption and re-emission can be calculated using the equation of radiation transport. The subscript  $\lambda$  indicates the wavelength dependency of  $L_{\lambda}$ . The solution for a homogeneous one-dimensional plasma can be given in analytic form [86]

$$L_{\lambda} = S_{\lambda} \left( 1 - e^{-\tau_{\lambda}} \right), \tag{2.1}$$

where  $S_{\lambda} = j_{\lambda}/\alpha_{\lambda}$  is the source function defined by the ratio of emissivity  $j_{\lambda}$  and the absorptivity  $\alpha_{\lambda}$ . Opacity is given by  $\kappa_{\lambda} = \alpha_{\lambda}/n_i$ , where  $n_i$  is the ion density. In local thermodynamic equilibrium (LTE), where the atomic levels are thermally populated, the source function  $S_{\lambda}$  equals the Planck blackbody function  $B_{\lambda}$ . We assume that such LTE holds for the high-density, strongly collisional Nd:YAG-driven plasma. In the exponent,  $\tau_{\lambda}$  is the wavelength-specific optical depth given by  $\tau_{\lambda} = \int \alpha_{\lambda} dx$ , where the absorptivity  $\alpha_{\lambda}$  is integrated over the plasma length. Rearranging Eq. (2.1) the optical depth of the observed plasma can be obtained from its spectral radiance via

$$\tau_{\lambda} = -\ln\left(1 - \frac{L_{\lambda}}{B_{\lambda}}\right),\tag{2.2}$$

with the relative spectral radiance  $L_{\lambda}/B_{\lambda}$ . The optical depth of plasmas of same temperature and density can only differ by a wavelength-independent factor  $a_i$ , here referred to as the relative optical depth, relating the plasmas' optical depths via  $\tau_{\lambda,i} = a_i \tau_{\lambda,0}$ . It follows from Eq. (2.2) that

$$\frac{L_{\lambda,i}}{B_{\lambda}} = 1 - \left(1 - \frac{L_{\lambda,0}}{B_{\lambda}}\right)^{a_i}.$$
(2.3)

It is instructive to use Eq. (2.3) to interpret the observed spectral changes, hypothesizing that plasma length scale is the pertinent parameter. At the wavelength  $\lambda_p$  of peak radiance near 13.5 nm, the optical depth typically has high values as follows from the work of Colgan *et al.* [29]. Their calculation results indicate a peak opacity value of ~5 × 10<sup>5</sup> cm<sup>2</sup>/g at a relevant 0.01 g/cm<sup>3</sup> ion density. Thus, taking a reasonable 20 µm plasma length [69], we deduce a typical value  $\tau_{\lambda_p} \approx 10$ . Next, as the plasma is heated under conditions of a spatially homogeneous laser illumination at constant intensity we can ascribe to it a single, constant temperature. The entire plasma surface thus has a radiance  $L_{\lambda_i}$  (in units of W sr<sup>-1</sup> m<sup>-2</sup> Hz<sup>-1</sup>) that is constant over the duration of the laser pulse. The observed spectra  $O_{\lambda,i}$  can be related to  $L_{\lambda_i}$  by further realizing that an opaque plasma will have a spectral radiance equal to that of a blackbody  $B_{\lambda,p}$  as here at 13.5-nm wavelength  $(\tau_{\lambda_p} \approx 10)$ . Thus, we equate  $O_{\lambda,p}/B_{\lambda,p} := 1 = L_{\lambda,p}/B_{\lambda,p}$ .

Using Eq. (2.3) any spectrum can be expressed in terms of any other spectrum via the relative optical depth  $a_i$ . The value of  $a_i$  can be obtained with respect to a chosen reference spectrum from a fit of Eq. (2.3) to the relative spectral radiance  $L_{\lambda,i}/B_{\lambda}$ . As reference, for which  $a_i = 1$ , the relative spectral radiance  $L_{\lambda,0}/B_{\lambda}$  of the spectrum with the narrowest main emission feature is used in the following, i.e., the one measured at 5 ns pulse duration and 16 µm droplet size. Typical literature values for the electron temperatures at which Nd:YAG LPPs most efficiently emit in-band radiation vary between 28 and 40 eV [29, 69, 79, 87]. A temperature in the center of this range of 34 eV is chosen for  $B_{\lambda}$  for all spectra. A common temperature, remains constant for all measurements. Variation of the blackbody temperature within the stated limits changes the fitted relative optical depth (see below) by less than 3%.



Figure 2.2: Relative spectral radiance  $L_{\lambda,i}/B_{\lambda}$  of experimental spectra taken at constant laser intensity but various laser pulse durations and droplet sizes (cf. Fig. 2.1). The relative spectral radiances are plotted as dotted curves with respect to the one of a reference spectrum  $L_{\lambda,0}/B_{\lambda}$  obtained at 5 ns laser pulse duration and 16 µm droplet diameter where the main emission feature at 13.5 nm is narrowest. For the blackbody function  $B_{\lambda}$  a temperature of 34 eV was used. The solid lines depict fits of Eq. (2.3) to the data featuring the relative optical depth  $a_i$  as single free fit parameter.

## 2.4 Results

Fig. 2.2 shows example data for  $L_{\lambda,i}/B_{\lambda}$  versus  $L_{\lambda,0}/B_{\lambda}$  for a wide range of droplet sizes and pulse durations. Excellent agreement of data and model fit is observed, featuring the relative optical depth  $a_i$  as single free fit parameter.

The values of the relative optical depth  $a_i$  as obtained from the procedure shown in Fig. 2.2 enable reproduction of spectra measured for other droplet sizes and laser pulse durations by radiation transport of the reference spectrum. Inserting the relative optical depth obtained from the fits into Eq. (2.3) and multiplying by  $B_{\lambda}$  leads to an excellent reproduction of experimental spectra as seen in Fig. 2.3(a) and 2.3(b). This is especially true for the main emission feature around 13.5 nm. When comparing the transported spectrum in the short-wavelength region between 5 and 12 nm, minor differences are visible. The differences are very small for increasing pulse duration in Fig. 2.3(a) and become slightly more pronounced for increasing droplet size in Fig. 2.3(b). This may be explained by changes in the plasma other than a simple linear optical depth such as emission from a multitemperature plasma or a slight dependence of plasma charge state distribution with droplet size and pulse



Figure 2.3: Comparison of the reference spectrum and radiation transported reference spectrum with the measured spectra. The reference spectrum was transported using Eq. (2.3) together with the relative optical depth as determined in Fig. 2.2. (a) Increasing laser pulse duration (b) Increasing laser pulse duration and droplet size. An additional spectrum is shown measured at lower laser intensity of  $1.1 \times 10^{11}$  W/cm<sup>2</sup> providing a better match with the radiation transported spectrum in the 5–12 nm range.

duration. Comparison of the relative intensities of the short-wavelength features suggests that the average charge state slightly increases with droplet size [76, 84]. To account for a possibly higher average charge state of the plasma at longer pulse duration and larger droplet size, the scaled reference spectrum may instead be compared to spectra taken at lower laser intensity. Indeed, comparing to spectra taken at a laser intensity of  $1.1 \times 10^{11}$  W/cm<sup>2</sup> shows excellent agreement over the entire spectral range measured. We thus observe that the short-wavelength band between 5 and 12 nm is a much more sensitive probe to the emission properties of Sn LPPs than the main emission feature at 13.5 nm.

In Fig. 2.4(a) the fitted values for spectra of all pulse durations and droplet sizes are summarized. The relative optical depth  $a_i$  appears to scale linearly with droplet radius and to strongly depend on the pulse duration. Linear fits are in good agreement with the data and converge to a common intercept of ~0.7 at zero droplet diameter. The slope coefficients monotonically increase with pulse duration from 0.017 to 0.025 and 0.030  $\mu$ m<sup>-1</sup> for 5, 15 and 25 ns, respectively.



Figure 2.4: (a) Dependency of the relative optical depth  $a_i$  on the droplet diameter for various laser pulse durations as obtained, e.g., in Fig. 2.2. The solid lines show a linear extrapolation of the data toward zero droplet size. (b) Experimental values for spectral purity (SP<sub>5.5-25.5nm</sub>) versus relative optical depth. The dashed line represents SP<sub>5.5-25.5nm</sub> as calculated from the radiation transported reference spectrum. The open diamond symbol indicates the SP<sub>5.5-25.5nm</sub> value of the radiation transported reference spectrum for a relative optical depth parameter  $a_i = 0.6$ , a value obtained from comparison of the radiation transported reference spectrum with the emission of the CO<sub>2</sub>-laser-driven plasma as shown in Fig. 2.5 (see text).

Having identified the optical depth as the pertinent scaling parameter for Nd:YAG-laser-produced tin plasmas the spectral purity of the emission spectrum is related to it in Fig. 2.4(b). Using this scaling all experimental  $SP_{5.5-25.5nm}$  values, calculated over a range of 5.5–25.5 nm as denoted in the subscript, collapse onto the gray dashed curve obtained by calculating the  $SP_{5.5-25.5nm}$  of the radiation transported reference spectrum.

It is instructive to compare the SP<sub>5.5–25.5nm</sub> scaling captured by the gray dashed curve with the SP value of spectra from a state-of-the-art, CO<sub>2</sub>-laser-driven EUV source. Such CO<sub>2</sub>-laser-driven plasmas may be expected to have small optical depths  $\tau < 1$  and thus less broadening, considering the 100-fold decrease in critical density compared to the Nd:YAG case. These CO<sub>2</sub>-laser-driven sources are, in general, characterized by relatively high SP and CE values. The spectrum was obtained (see Fig. 2.5) by pre-deforming a droplet by a low-intensity CO<sub>2</sub> laser *prepulse*, leading to a disk-shaped target of approximately 200 µm in diameter. The flat target was subsequently irradiated by a high-intensity, 100 ns, 320 mJ *main pulse* with a beam size that matched the target to produce EUV radiation. In this



Figure 2.5: Comparison of the transported reference spectrum using Eq. (2.3) with  $a_i = 0.6$  and the spectral emission from a CO<sub>2</sub>-laser-driven plasma.

case, the spectrum was taken over a wavelength band spanning 6.8–16.7 nm. The fraction of light emitted in the 2% bandwidth around 13.5 nm relative to the total spectral energy in this measured bandwidth is SP<sub>6.8nm-16.7nm</sub> = 23%. For a relative optical depth  $a_i = 0.6$ , the Nd:YAG reference spectrum is found to closely match this SP<sub>6.8nm-16.7nm</sub> performance (also see Fig. 2.5). Over the extended wavelength band of 5.5–25.5 nm that defines SP in this work, this scaled Nd:YAG LPP spectrum has SP<sub>5.5–25.5nm</sub> = 16.5% (open diamond symbol in Fig. 2.4(b)). The reference spectrum for  $a_i = 0.6$  closely resembles the CO<sub>2</sub> spectrum. This is a remarkable finding as the plasma conditions for the two cases are vastly different and the conditions of LTE and  $\tau \gg 1$  required for the procedure outlined in this work are not met for the CO<sub>2</sub> case.

Calculating the maximally obtainable conversion efficiency via CE = SP/2 [69, 84] a significantly higher CE value is expected for  $CO_2$ -driven LPPs, given its higher SP. However, accounting for the fraction of laser light  $\epsilon$  absorbed by the tin target near unity (> 0.9 [70]) for the case of  $1 \,\mu m$  radiation, while about 0.7 for  $10 \,\mu m$ light [88]—both drive laser cases may indeed have about the same conversion efficiency limit of  $CE = \epsilon SP_{5.5-25.5nm}/2 \approx 6\%$  making 1 µm solid-state lasers a viable alternative as source drive lasers. Naturally, the maximum obtainable CE depends not only on the emission spectrum as there are further significant contributions to the total energy balance, aside from a finite emission anisotropy. Examples include plasma kinetics, ionization energy, as well as contributions from plasma emission outside the 5.5–25.5 nm range. A careful comparison of this total energy balance is required between the CO2 and Nd:YAG drive laser cases. Further, a central requirement is the creation of manageable amounts of debris from the plasma. This entails, among others, fragments or high-energy particles that could reduce optics lifetime. Laser energy not contributing to radiation may instead lead to the production of fast ionic debris and possible gains in spectral purity and radiative output power should be carefully weighed out against, e.g., increases in the tin load on the optical components. A full quantification of the loads of various debris is left for future work.

## 2.5 Conclusion

In conclusion, optical depth is established to be the pertinent scaling parameter in high-density laser-produced plasmas from tin-microdroplets. Observed changes in the experimental emission spectra from plasmas of various droplet sizes as well as various laser pulse durations are remarkably well described using a one-dimensional radiation transport equation featuring the relative optical depth of the plasma as sole parameter. The excellent description of the experimental data by the model suggests that a dominant fraction of the EUV emission may be produced in a singledensity, single-temperature region of the plasma because the underlying opacity does not appear to change. The here established scaling with optical depth indicates that Nd:YAG LPPs may suffer from strong absorption and re-emission significantly redistributing the spectral energy into wavelength-bands other than 13.5 nm in case of large plasma size. Therefore, the optical depth of these light sources needs to be minimized to reach highest SP values which can be done by reduction of laser pulse duration and droplet size. In such optimized cases, and accounting for the difference in laser absorptivity, CE values of Nd:YAG-driven plasma may well rival those of state-of-the-art CO<sub>2</sub>-driven plasma sources.

## 3 | Extreme ultraviolet light from a tin plasma driven by a 2-μm-wavelength laser

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An experimental study of laser-produced plasmas is performed by irradiating a planar tin target by laser pulses, of 4.8 ns duration, produced from a KTP-based 2-µmwavelength master oscillator power amplifier. Comparative spectroscopic investigations are performed for plasmas driven by 1-µm- and 2-µm-wavelength pulsed lasers, over a wide range of laser intensities spanning  $(0.5-5) \times 10^{11}$  W/cm<sup>2</sup>. Similar extreme ultraviolet spectra in the 5.5–25.5 nm wavelength range and underlying plasma ionicities are obtained when the intensity ratio is kept fixed at  $I_{1µm}/I_{2µm} =$ 2.4(7). Crucially, the conversion efficiency of 2-µm-laser energy into radiation in the industrially relevant 2% bandwidth centered at 13.5 nm is found to be a factor of two larger, at a representative 60° observation angle, than in the case of the denser 1-µm-laser-driven plasma.

#### 3.1 Introduction

Extreme ultraviolet (EUV) lithography has successfully entered high-volume manufacturing, enabling the continued miniaturization of semiconductor devices. The required EUV light is generated from mass-limited tin-microdroplet laser-produced plasma (LPP) [11, 12, 80, 82, 83]. Multiply-charged tin plasma ions are the atomic sources of EUV radiation near 13.5 nm wavelength [12, 18, 19, 23, 24, 27, 29, 30]. Currently, CO<sub>2</sub>-gas lasers operating at  $\lambda = 10.6 \,\mu\text{m}$  wavelength are used to drive the EUV-emitting plasma at a high conversion efficiency (CE) of laser energy into in-band radiation, i.e., in a 2% wavelength bandwidth centered at 13.5 nm emitted into the hemisphere back towards the laser that is relevant for state-of-the-art EUV lithography. Solid-state lasers, operating at near- or mid-infrared wavelengths, may however become a viable alternative in the future. Such laser systems would potentially provide a smaller footprint, a significantly higher efficiency in converting electrical power to laser light, and may be scaled to much higher pulse energies and output powers which will enable even more powerful EUV light sources. However, the shorter drive laser wavelength of, e.g., the well-known Nd:YAG laser  $(1.064 \,\mu m)$  is associated with large optical depths originating from a high critical plasma density [80]. Large optical depths may strongly limit the efficiency of such Nd:YAG-driven sources as opacity effects broaden the EUV spectrum well beyond the 2% wavelength acceptance bandwidth, thus reducing the spectral purity (SP) of the EUV plasma source [44-47, 62, 84, 89, 90]. SP is defined here as the ratio of in-band EUV energy to the total energy emitted in the 5.5–25.5 nm range. Simulation efforts indicate that a global optimum of the efficiency of converting drive laser light into useful EUV radiation lies in between the well-known 1- and 10-µm cases [91]. In this range, thulium lasers, operating at 1.9-µm wavelength, appear promising [16]. However, no experimental studies of plasmas driven by lasers in this wavelength range, under conditions relevant for EUV emission, are yet available. In this work we present a study of the EUV emission spectrum of a 2-µm-wavelength-LPP generated from a planar-solid tin target. The laser light is obtained from a master oscillator power amplifier (MOPA) based on a series of KTP crystals pumped by a Nd:YAG laser. This setup enables assessing the potential of thulium lasers without the expense of building and fielding one. The obtained EUV spectra and CE are compared to those obtained from Nd:YAG-LPP under otherwise very similar conditions.

## 3.2 Experimental setup

In this work we present an experimental study of an LPP generated by illuminating a planar-solid tin target of 99.995% purity with lasers having wavelengths of  $1 \,\mu\text{m}$  and  $2 \,\mu\text{m}$ . The target is mounted on a two-axis translation stage inside a vacuum chamber pumped to  $1 \times 10^{-6}$  mbar. The target is moved after illumination by two laser pulses to prevent crater formation influencing the EUV emission. Spectral emission in the 5–25 nm range is recorded by means of a transmission grating spectrometer positioned at 60 degrees with respect to the incoming laser (see Fig. 3.1). The spectrometer is operated with a slit width of  $25 \,\mu m$  and a  $10\,000$  lines/mm grating. The dispersed light is collected on a back-illuminated charge coupled device and is post-processed, correcting for the camera's quantum efficiency and grating dispersion efficiency. More details on the spectrometer and post-processing of the images are provided in Ref. [68] and [84]. To obtain the absolute amount of EUV radiation emitted in a 2% bandwidth around 13.5 nm, a calibrated EUV photodiode assembly [84] is used. It is installed at an angle of  $-60^{\circ}$ , mirroring the alignment of the spectrometer, see Fig. 3.1(a). This photodiode assembly consists of a Mo/Si multilayer mirror that reflects the in-band radiation onto a photodiode. The photodiode is coated with a Si/Zr coating in order to block infrared light.

The 2-µm light source comprises a KTP-based MOPA operated in type-2 phase matching following the approach of Arisholm et al. [92]. The MOPA setup is pumped at a 10 Hz repetition rate by a seeded Q-switched Nd:YAG laser (Quanta-Ray 250-10 PRO) providing pulses of 10 ns duration (at full width at half maximum, FWHM). First, a 2170 nm idler seed beam of 1.8 mJ energy is created in a singly-resonant optical parametric oscillator (OPO). To create this seed beam, 18 mJ of the pump light is demagnified to a beam diameter of 1.5 mm and is coupled into the OPO which is operated in a collinear alignment. About 20% of the pump radiation is converted into a 2090-nm-wavelength signal beam and a 2170 nm idler beam. At the exit of the OPO a dichroic mirror separates the signal and idler beams from the remaining pump radiation. The idler beam is subsequently expanded to 11 mm in diameter to seed the OPA, while the signal beam is removed through polarization optics. The OPO and OPA are pumped by the same laser. To achieve the highest efficiency in the OPA, 1.3 J of the pump laser light is delayed by 1.3 ns and is reduced to a beam size of 10 mm in diameter. Seed and pump beams are overlapped on a dichroic mirror after which they pass three 18-mm-long KTP crystals. The crystal orientation is alternated to compensate for walk-off. A total energy of 260 mJ is achieved in signal and idler combined. Pump and signal beams are separated from the idler using a dichroic mirror and polarization optics, respectively. To adjust the idler beam energy a combination of half-wave plate and polarizer is installed before it is focused onto the tin target. The size of the focal spot is  $72 \times 128 \,\mu\text{m}$  (FWHM). The asymmetry in the focal spot size is caused by the slightly higher beam quality



Figure 3.1: (a) Schematic representation of the experimental setup. A master oscillator power amplifier (MOPA) setup, comprising an optical parametric oscillator (OPO) and an optical parametric amplifier (OPA), is pumped by a Nd:YAG laser. The 2- $\mu$ m-idler beam from the MOPA is focused onto a planar-solid tin target to create plasma. The EUV emission from the plasma is captured by a transmission grating spectrometer and a calibrated EUV photodiode. (b) Spatial and (c) temporal profiles of the 1- $\mu$ m and 2- $\mu$ m drive lasers.

on the horizontal, *x*-axis of the beam (cf. Fig. 3.1(b)). The temporal pulse duration is 4.8 ns (FWHM). Uncertainties in determining the FWHM pulse duration are at or below 0.5 ns. The pulse has a short rise time of  $\sim$ 1 ns whereas its fall time is significantly longer and is seen to follow the pulse shape of the seed beam.

A seeded, in-house built Nd:YAG laser is used as the 1- $\mu$ m-laser light source to drive plasma [73]. The laser employs two electro-optical modulators to create temporal profiles of the desired shape. Here the temporal profile was shaped to match that of the idler of the MOPA (see Fig. 3.1(c)). A lens is used to focus the laser beam onto the tin target to a symmetric spot size of 66  $\mu$ m (FWHM) closely matching the beam spot size of the idler beam in the measurement plane (see Fig. 3.1(b)).

### 3.3 Results

In the following, we assess the potential of a 2-µm-wavelength tin-plasma driver by studying the spectral characteristics with emphasis on EUV in-band radiation. Fig. 3.2(a) shows EUV spectra obtained when the beam intensity  $I_{2\mu m}$  is varied in a (0.2–1.9) × 10<sup>11</sup> W/cm<sup>2</sup> range. The intensity of the 2-µm driver  $I_{2\mu m}$  is given by the peak intensity in time and space by  $I_{2\mu m} = (2\sqrt{2\ln 2/2\pi})^3 E_{2\mu m}/abt_p$ . Here,  $E_{2\mu m}$  is the laser energy, *a* and *b* are the Gaussian FWHM sizes along the major and minor axis of the elliptical beam, and  $t_p$  is the FWHM pulse duration. Spectral features belonging to Sn<sup>5+</sup>–Sn<sup>15+</sup> are observed in the studied spectral range [18, 21, 23, 29, 76, 93]. At the lower laser intensities, spectral features belonging to Sn<sup>5+</sup>–Sn<sup>8+</sup> are visible. At higher laser intensities, spectral features related to the higher charge states Sn<sup>10+</sup>–Sn<sup>15+</sup> are prominent. Spectral emission from these charge states also becomes visible in the short-wavelength region of the spectra below 12 nm. The evolution of spectral features in this wavelength regime gives direct qualitative insight into the underlying charge state distribution as the contributions from the individual charge states can be identified [76].

For comparison, in Fig. 3.2(b) a set of spectra is presented that was obtained using the 1-µm-wavelength driver. Emission spectra are obtained for beam intensities  $I_{1\mu m}$  ranging (0.4–4.4) × 10<sup>11</sup> W/cm<sup>2</sup>.  $I_{1\mu m}$  is defined analogously to  $I_{2\mu m}$ . The beam intensities are selected such that similar short-wavelength features are obtained as in the respective 2-µm cases. The laser intensity at which any particular charge state distribution is obtained, is lower for the 2-µm case by about a factor of two. The evolution of spectral features with laser intensity appears to be similar, comparing Fig. 3.2(a) and 3.2(b).

To study this difference in more detail, pairs of intensities  $I_{1\mu m}$  and  $I_{2\mu m}$  were chosen such that the short-wavelength spectral features, ranging from 6–10 nm, in the respective emission spectra are best matching. In Fig. 3.2(c), the ratio of thus selected pairs  $I_{1\mu m}/I_{2\mu m}$  is plotted versus  $I_{1\mu m}$ . On average the 1-µm-driver requires a constant factor 2.4(7) higher intensity to reach the same effective charge state distribution of the plasma when compared to the 2-µm case. The number in brackets in the ratio 2.4(7) indicates the overall uncertainty which is dominated by systematic uncertainty. Naively, one would perhaps rather expect this ratio to be closer to a value of four given (i) the  $n_c \propto \lambda^{-2}$  dependency of the critical electron density  $n_c$  on drive laser wavelength  $\lambda$ ; (ii) the approximately linear scaling of the local emission intensity (which in steady state equals laser absorption and hence  $\propto I$ ) with ion density  $n_i$ ; and (iii) that  $n_i \sim n_c$  at equal charge state distribution. This would lead to  $n_i \sim n_c \propto \lambda^{-2}$ . To achieve equal temperatures, one would thus expect a scaling of required laser intensity with wavelength  $I \propto \lambda^{-2}$ . Studies on quasi-stationary ablation fronts [41] relevant for our current investigations with



Figure 3.2: Spectra from plasma produced from a planar-solid tin target irradiated with laser pulses at various intensities of the (a) 2-μm-driver of 4.8 ns duration and Gaussian spot size of 72×128 μm. The emission features attributed to the various Sn ions are labeled by the respective charge state. (b) Spectra from tin plasma driven by a 1-μm-beam of 4.4 ns pulse duration and Gaussian spot size of 66×66 μm. The gray vertical band indicates a 2% bandwidth centered at 13.5 nm. (c) Ratio of intensities of 1- and 2-μm-drive laser beams needed to obtain spectra with matching short-wavelength features. The red line indicates the average ratio.

#### Results

significant laser absorption in the underdense coronal region, before the critical surface, instead indicate a scaling of a typical density  $n_i \propto \lambda^{-1}$  and, thus,  $I \propto \lambda^{-1}$ , all other factors remaining constant over the absorption path (see Eq. (31) in Ref. [41]). This latter scaling is fully in line with our current findings and sheds light on the physics origins of the plasma-emission of EUV light. Further radiation-hydrodynamic simulations are however required to investigate the details of the evolution of the relevant plasma conditions and their dependence on drive laser wavelength.

In Fig. 3.3(a) the CE is plotted versus drive laser intensity for the 1- $\mu$ m and 2um cases. The measured in-band radiation is extrapolated from the measurement at 60° to the  $2\pi$  steradian hemisphere facing the laser origin, assuming isotropic emission over this half-sphere. From literature, it is evident that the EUV emission from LPPs from planar-solid targets has a some angular anisotropy [49]. Several studies have indicated that the angular dependence of EUV emission is nearly independent on the focal spot size and the pulse duration [49, 52, 94]. For this reason, our observations are not expected to be dominated by any small remaining differences in laser beam characteristics which were carefully matched in our experiments. Changing the drive wavelength for a tin-LPP on a planar-solid target from 266 nm to 1  $\mu$ m was found to lead to a reduced angular dependence of the inband emission [75]. For droplet targets, a  $10-\mu$ m-driven LPP was shown to exhibit only a slightly reduced angular dependence of the in-band emission in comparison to the 1- $\mu$ m-driven LPP [95] and thus the relatively small step to 2- $\mu$ m laser radiation is not expected to change the current EUV emission anisotropy significantly. We furthermore note that the observation under the current, relatively large angle of 60° constitutes a representative measure of the overall CE [49, 52, 84, 94].

The open markers in Fig. 3.3(a) indicate data obtained from the absolute inband response of the spectrometer. Here, the in-band counts of the spectrometer are calibrated by means of the EUV photodiode. The CE of the 2- $\mu$ m-LPP rises with beam intensity, up to a maximum value of 3.1% at a laser intensity of  $1.0 \times 10^{11}$  W/cm<sup>2</sup>. When further increasing the laser intensity CE decreases. For the 1- $\mu$ m case, a similar rise of CE with increasing beam intensity is observed, with a maximum CE reaching 1.7%, i.e., only about half that of the 2- $\mu$ m case. The maximum CE for the 1- $\mu$ m-LPP is reached at a laser intensity of  $3.0 \times 10^{11}$  W/cm<sup>2</sup>. No decrease in CE is observed when moving to higher laser intensities, within the probed parameter space. Comparing the two drive laser cases, the relative difference in maximum CE amounts to a factor 1.8. The 1- $\mu$ m-LPP requires significantly higher intensities to reach optimum CE. This is in line with the findings presented in Fig. 3.2(c).

Fig. 3.3(b) shows the spectral purity of both the  $1-\mu m$  and the  $2-\mu m$ -LPPs as a function of laser intensities. Both SP data sets show a behavior that is similar to that of the corresponding CE curves. Note again that SP is here defined as the ratio



Figure 3.3: Comparison of tin plasma emission characteristics for the 1- and 2-μmdrivers: (a) Dependency of conversion efficiency (CE) on drive laser intensity for both drivers. The plot shows CE directly captured by a calibrated EUV photodiode, mounted under a 60 degree angle (cf. Fig. 3.1), as well as CE obtained from the absolute in-band response of the spectra, all assuming isotropic emission. (b) Spectral purity (SP) versus the intensity of the corresponding drive laser. (c)– (e) Juxtaposition of emission spectra for the two laser cases at three different intensities. The spectral counts of the spectrometer are divided by the drive laser energy.

of in-band EUV energy to the total energy emitted in the 5.5–25.5 nm range. The maximum SP of the 2- $\mu$ m-LPP is at 7.4%, a factor 1.8 larger than the value of the 1- $\mu$ m-LPP with a maximum of 4.2%. The ratio of the maximum SP's is identical to the ratio of the maximum CE's. This indicates that the discrepancy in conversion efficiency can be attributed to the decreased SP of the 1- $\mu$ m-LPP. Figures 3.3(c)–3.3(e) show pairs of matching emission spectra, i.e., plasmas having similar ionicities. Panel 3.3(c) depicts the 2- $\mu$ m-LPP spectrum with the highest CE. All spectra have been divided by the drive laser energy. The out-of-band features are seen to match well. It is apparent that a significant amount of spectral emission between 13 nm and 15 nm is missing in the 1- $\mu$ m case compared to the 2- $\mu$ m-LPP. This lack of emission in the unresolved transition array at 13.5 nm explains the reduced CE of the 1- $\mu$ m-LPP.

To qualitatively explain the significant differences observed between the two drive laser cases, it is instructive to employ an intuitive two-zone radiation transport model. In this model, the emission from a hot plasma core zone ('zone 1') traverses a plasma zone ('zone 2') at a modestly lower density and temperature. Such a two-zone plasma approximates our experimental conditions using a laser beam with a Gaussian spatial intensity profile which inhomogeneously heats the plasma. The second zone will contribute to the overall emission but will also partially absorb the light emitted from the first zone [96, 97]. Following Ref. [89], the spectral radiance  $L_{\lambda}$  of a homogeneous, one-dimensional plasma is given by  $L_{\lambda} = B_{\lambda} (1 - e^{-\tau_{\lambda}})$ . Here  $B_{\lambda}$  is the Planck source function, assuming local thermodynamic equilibrium (LTE) conditions. The subscript  $\lambda$  indicates the wavelength dependency of  $L_{\lambda}$ . In the exponent,  $\tau_{\lambda}$  is the wavelength-specific optical depth [12, 89]. The expected density and temperature values support our LTE approach (see, e.g., Ref. [12]) and small deviations from it do not meaningfully impact our qualitative analysis in the following. We now expand the model by adding a second layer of plasma. The first plasma layer emits the spectral radiance  $L_{\lambda,1}$  over an optical depth  $\tau_{\lambda,1}$ . This light subsequently traverses a second plasma layer with an optical depth  $\tau_{\lambda,2}$ . The total spectral radiance  $L_{\lambda,2}$  exiting the second layer of plasma is given by

$$L_{\lambda,2} = B_{\lambda,1} \left( 1 - e^{-\tau_{\lambda,1}} \right) e^{-\tau_{\lambda,2}} + B_{\lambda,2} \left( 1 - e^{-\tau_{\lambda,2}} \right), \tag{3.1}$$

where  $B_{\lambda,1}$  and  $B_{\lambda,2}$  are the respective blackbody functions of the two plasma layers. Next, we take two spectra obtained from plasma driven by 2-µm-laser light. These two spectra serve as base spectra for the model's two plasma layers [89]. Both spectra are, for simplicity, assumed to be generated from a single density-temperature plasma layer with significant optical depth ( $L \approx B$  at peak emission) of value  $\tau_{\lambda,i} \cdot a_i$  (i = 1, 2 for zones 1 and 2) with a constant multiplication factor  $a_i$  accounting for differences in density or length scales following the approach of Schupp *et al.* [89].



Figure 3.4: Tin spectra from plasmas driven by 1- and 2-µm-lasers. The blackbody functions  $B_{\lambda,1}$  and  $B_{\lambda,2}$  are divided by  $B_{13.5 \text{ nm},1}$ . The 2-µm-LPP spectra are scaled to be confined by their respective blackbody functions. The 1-µm-LPP spectrum is scaled with the same factor as the  $1.0 \times 10^{11} \text{ W/cm}^2$ , 2-µm spectrum (cf. Fig. 3.3(d)). The green curve depicts the fit result of Eq. (3.1) to the 1-µm-LPP spectrum (see main text). The inset schematically depicts the model.

In the following, the base spectrum of the first zone is associated with the maximum CE (cf. Fig. 3.3(d)). The base spectrum for the second zone is chosen from a modestly lower laser intensity, corresponding to a modestly lower plasma temperature conform our model. Following Ref. [12] the effective temperature of the first zone is set to 32 eV associated with optimum plasma conditions for producing in-band EUV light at the here expected plasma densities [12]. The plasma temperature of the second zone is subsequently found by matching the relative intensity values of the two base spectra at 13.5 nm wavelength (as  $L \approx B$  at peak emission given the large optical depths involved [12, 89]). This results in a temperature of 29 eV for the second zone. The multiplication factors  $a_i$  are used as free fit parameters, including an additional overall amplitude scale factor. Fig. 3.4 shows the result of a least-squares fit of the model function Eq. (3.1) to the measured 1-µm-driven spectrum at a  $2.5 \times 10^{11}$  W/cm<sup>2</sup> laser intensity that reproduces the ionicity of the  $2-\mu$ m-driven base spectrum (see Fig. 3.3(d)). The model is seen to excellently reproduce the data. The fit parameters obtained are  $a_1 = 1.3$  and  $a_2 = 0.7$ , close to unity value such that the original base spectra are already representative of the emission of the two zones. A more quantitative interpretation of these fit values is not currently warranted given the qualitative nature of the model application. A comprehensive explanation of the generic effects of a two-zone plasma is provided in Ref. [96] albeit for hotter and denser plasma. EUV radiation, produced in the hottest part of the plasma, passes through regions of underheated plasma generated by the lower-intensity parts of the Gaussian laser intensity profile. The EUV emission in the case of the 1- $\mu$ m-drive laser occurs at a higher plasma density than that of the 2- $\mu$ m-driver and also its underheated plasma zone will have higher ion density. Hence, the 1- $\mu$ m-LPP exhibits a higher EUV self-absorptivity in the underheated zone making the 2- $\mu$ m-LPP here the more efficient emitter of in-band EUV radiation.

## 3.4 Conclusion

In conclusion, conversion efficiencies in excess of 3%, assuming isotropic emission of the in-band EUV radiation, have been achieved from a Sn plasma driven by a  $2-\mu$ m-wavelength laser system, outperforming plasmas driven by a  $1-\mu$ m-laser by a factor of two. The difference between the two drive laser cases can furthermore be qualitatively explained from self-absorption effects and their impact on spectral purity. Further increases in CE are to be expected when providing a homogeneous heating of the plasma, optimizing the spatio-temporal intensity profile of the drive laser. Such future studies, preferably executed on mass-limited droplet targets and including measurements of the full angularly resolved EUV emission characteristics, will further pave the way for the application of  $2-\mu$ m drive lasers in industrial sources of EUV radiation powering tomorrow's nanolithography.

## 4 | Characterization of 1- and 2-μm-wavelength laser-produced microdroplet-tin plasma for generating extreme ultraviolet light

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Experimental spectroscopic studies are presented, in a 5.5–25.5 nm extreme ultraviolet (EUV) wavelength range, of the light emitted from plasma produced by the irradiation of tin microdroplets by 5-ns-pulsed, 2-µm-wavelength laser light. Emission spectra are compared to those obtained from plasma driven by 1-µmwavelength Nd:YAG laser light over a range of laser intensities spanning approximately  $(0.3-5) \times 10^{11} \text{ W/cm}^2$ , under otherwise identical conditions. Over this range of drive laser intensities, we find that similar spectra and underlying plasma charge state distributions are obtained when keeping the ratio of 1-um to 2-um laser intensities fixed at a value of 2.1(6), which is in good agreement with RALEF-2D radiation-hydrodynamic simulations. Our experimental findings, supported by the simulations, indicate an approximately inversely proportional scaling  $\propto \lambda^{-1}$ of the relevant plasma electron density, and of the aforementioned required drive laser intensities, with drive laser wavelength  $\lambda$ . This scaling also extends to the optical depth that is captured in the observed changes in spectra over a range of droplet diameters spanning 16–51 µm at a constant laser intensity that maximizes the emission in a 2% bandwidth around 13.5 nm relative to the total spectral energy, the bandwidth relevant for EUV lithography. The significant improvement of the spectral performance of the 2- $\mu$ m- vs 1- $\mu$ m-driven plasma provides strong motivation for the development of high-power, high-energy near-infrared lasers to enable the development of more efficient and powerful sources of EUV light.

## 4.1 Introduction

Laser-driven microdroplet-tin plasma provides the extreme ultraviolet (EUV) light that is used in state-of-the-art EUV lithography [11, 18, 31, 32, 80-82]. Ever more powerful sources of EUV light are required for future lithography applications. This EUV light is generated from electronic transitions in multiply charged tin ions that strongly emit radiation in a narrow band around 13.5 nm [19, 21-27, 29, 30, 93]. EUV-emitting plasma in an industrial nanolithography machine is driven by CO<sub>2</sub>gas lasers with a  $10-\mu m$  wavelength. Such plasma achieves particularly high conversion efficiencies (CE) of converting drive laser light into EUV radiation in a 2-% wavelength bandwidth around 13.5 nm, the so-called in-band radiation, that can be transported by the available Mo/Si multilayer optics [10, 40]. Near- or mid-infrared solid-state lasers may however soon become an attractive alternative to the CO<sub>2</sub>-gas lasers because such modern solid-state lasers are expected to have a significantly higher efficiency in converting electrical power to laser light. Furthermore, they may reach much higher pulse energies and output powers, in turn enabling more EUV output. Big Aperture Thulium (BAT) lasers [16, 98] represent a particularly promising class of novel, powerful laser systems that have recently drawn significant attention. These lasers would operate at 1.9-µm wavelength, in between the well-known cases of 1- and 10-µm drive lasers. Recent simulation work indicates that a global CE optimum lies within this range of 1- and 10-µm drive laser wavelength [91]. Briefly, such studies point out that the longer-wavelength drivers are associated with sub-optimal absorption of the laser energy by the plasma whereas shorter-wavelength drivers may exhibit severe opacity broadening of the EUV spectrum out of the 2-% acceptance bandwidth [62, 89, 90]. To date, no experimental studies of mass-limited, microdroplet-tin-based plasmas driven by lasers in this wavelength range are however available to verify these claims.

In this article a study of the EUV emission spectrum of 2-µm-wavelength-laserdriven tin-microdroplet plasma is presented. The laser light is obtained from a master oscillator power amplifier setup that comprises a series of KTP crystals pumped by a ns-pulsed Nd:YAG laser ( $\lambda \approx 1 \mu$ m), enabling one to gauge the potential of, e.g., thulium lasers without the effort of building one. The recorded spectroscopic data are compared to those obtained from a 1-µm-driven plasma under otherwise identical conditions, over a wide range of droplet sizes and laser intensities. Radiationhydrodynamic simulations using the RALEF-2D code [17], are presented to support the experimental findings. Following the recent work of Schupp *et al.* [89] on Nd:YAG-laser-pumped plasma, an analytical solution for radiation transport in an optically thick one-dimensional plasma is used to quantify the influence of optical depth on the broadening of the key emission feature at 13.5 nm.

### 4.2 Experiment

In the first set of experiments micrometer-sized liquid tin droplets are irradiated with high-intensity 2-µm-wavelength laser pulses produced in a master oscillator power amplifier (MOPA). Following the work of Arisholm et al. [92], the MOPA consists of a singly resonant optical parametric oscillator (OPO) in collinear alignment followed by an optical parametric amplifier (OPA). The latter comprises two 18-mm long KTP crystals operated in type II phase matching. The setup (see Fig. 4.1) is pumped by a seeded Nd:YAG laser with a spatially flat-top and a temporally Gaussian profile of 10 ns (FWHM). The OPO is pumped with 18 mJ of energy within a 1.5-mm-diameter beam resulting in an idler beam energy of 1.8 mJ at a wavelength of 2.17 µm. The OPO is operated slightly off its degeneracy point to minimize back conversion of signal and idler into the pump wavelength, a process which reduces beam quality of both beams. After the OPO the signal beam is removed and the idler beam expanded to 11 mm and amplified in the OPA. Using 1.3 J of pump energy within a beam diameter of 10 mm, 260 mJ of  $2-\mu$ m radiation are obtained, summing signal and idler pulse energies. The pulse duration of both beams after amplification is 4.3 ns.

For the experiments the signal beam is removed via polarization optics and solely the idler beam is used. The idler beam is focused onto several ten-micrometer-sized liquid tin droplets created via coalescence of even smaller microdroplets from a tin jet in a vacuum chamber that is kept at or below  $10^{-6}$  mbar. The diameter of the microdroplets is adjustable within a range from  $16-51 \,\mu\text{m}$ . The focal spot is elliptical and has a size of 65×88 µm (FWHM) and laser intensities of up to  $2.1 \times 10^{11}$  W/cm<sup>2</sup> are obtained on the tin droplets. Data taken with this 2-crystal setup is used for Sec. 4.4 and is part of the data in Fig. 4.2(c). The intensity is defined as peak intensity in time and space and calculated to  $I_{\rm L}$  =  $(2\sqrt{2\ln 2/2\pi})^3 E_{\rm L}/abt_{\rm p}$  with laser energy  $E_{\rm L}$ , FWHMs *a* and *b* along the major and minor axis of the bivariate Gaussian and pulse duration  $t_{p}$ . The energy in the beam is adjusted by the combination of a half-waveplate and polarizer. The data displayed in Fig. 4.2(a) was taken in a later experiment and after installation of a third crystal in the OPA which increased the energy in signal and idler combined to 360 mJ while the pulse duration increased slightly to 4.7(3) ns (FWHM). The produced beam has a symmetric focal spot and measurements are obtained for three focal spot sizes of 106, 152 and 194  $\mu$ m (FWHM) that are obtained using lenses of different focal distance length. The data obtained in the first and this later experiment is combined in Fig. 4.2(c).

To enable a direct comparison with plasmas driven by  $1-\mu m$  wavelength laser pulses, light from the  $1-\mu m$  pump laser is redirected before entering the MOPA and is focused onto the tin droplets instead. Again, a combination of a half-wave plate and polarizer allows for adjustment of the beam energy. The focal spot has



Figure 4.1: Schematic representation of the experimental setup. A master oscillator power amplifier (MOPA) setup, comprising an optical parametric oscillator (OPO) and an optical parametric amplifier (OPA), is pumped by a Nd:YAG laser (blue line). The signal beam is separated via polarization optics and the idler beam ( $\lambda = 2.17 \mu$ m) is focused onto tin microdroplets within a vacuum chamber. EUV emission is captured by a transmission grating spectrometer positioned at 60° with respect to the laser axis. An additional, third KTP crystal (dashed outline) was used in the OPA in a subset of the experiments.

a symmetric Gaussian shape of  $86 \,\mu\text{m}$  (FWHM). The EUV emission from the tin plasma is collected by a transmission grating spectrometer [68] set up under a  $60^{\circ}$  angle with respect to the incoming laser beam. The spectrometer was operated with a 10 000 lines/mm grating, a 25  $\mu$ m slit and without filter. The measured spectra are corrected for the grating's first and second order diffraction efficiency as well as for the quantum efficiency of the camera. The wavelength is calibrated in a separate experiment using atomic line emission from an aluminum plasma. Spectral purity (SP), defined as the ratio of spectral energy in a 2% bandwidth around 13.5 nm to the total EUV energy, is used to characterize the EUV light source. All SP values provided are calculated with respect to the measured spectral range of 5.5–25.5 nm.

## 4.3 Scaling of spectral features with laser intensity and wavelength

For defining development targets regarding power and pulse energy of future 2- $\mu$ m lasers for use in EUV light sources, it is particularly relevant to know the laser intensity needed to obtain a tin charge state balance optimal for the production of 13.5-nm light. In this section the laser intensity on the tin droplet is scanned and the optimal laser intensity determined as the value at which SP is highest, given that SP is the ultimate limit of CE as follows from energy conservation CE<SP/2

for isotropic emission [84]. To better understand the relevant plasma temperatures and densities, we study the ratio of 1- and 2- $\mu$ m laser intensities at which plasmas of equal temperatures are established. Plasma temperature is experimentally established via the shape and amplitude of charge state specific spectral emission features [20, 76, 99, 100]. These features are indicative of the plasma's charge state distribution which is predominantly dependent on plasma temperature [41]. The experimental results are then compared to computer simulations using the radiation-hydrodynamic code RALEF-2D as well as to previous analytic work [41].

### Spectral dependencies on drive laser intensity

In the experiments, first the idler beam from the MOPA is focused onto a 30-µmdiameter droplet and spectra are measured using the 106-µm spot size at multiple intensities within a range of  $(0.1-2.2) \times 10^{11}$  W/cm<sup>2</sup> (see Fig. 4.2(a)). At the lowest laser intensity the plasma strongly emits around 14.5 nm and distinct 4d-4f transitions in Sn<sup>6+</sup> are visible around 17 nm [100]. Emission between 18–20 nm can be mainly attributed to Sn<sup>5+</sup>. At 15.7 nm, a strong emission feature from 4d-4f and 4p-4d transitions in Sn<sup>7+</sup> is visible. Going up this 'ladder' of charge states, emission from 4d-4f and 4p-4d transitions in  $\text{Sn}^{8+}$  is visible at 14.8 nm and from  $\text{Sn}^{9+}$ at 14.2 nm. With increasing laser intensity the average charge state of the plasma increases and emission from  $Sn^{10+}$  is evident in the 9.5–10 nm region [76]. Increasing laser intensity beyond  $10^{11}$  W/cm<sup>2</sup>, the plasma strongly emits at 13.5 nm. This emission originates from the 4d-4f, 4d-5p and 4p-4d unresolved transitions arrays (UTAs) in  $Sn^{8+}$ – $Sn^{14+}$  [18, 21]. With the strong emission at 13.5 nm, charge state specific features become visible between 7 and 12 nm. These features belong to the same  $\text{Sn}^{8+}$ - $\text{Sn}^{14+}$  ions and here the 4d-5f, 4d-6p and 4p-5s transitions contribute strongest [20, 76]. With increasing laser intensity SP rises to values of 15% at  $0.8 \times 10^{11}$  W/cm<sup>2</sup> where charge state balance is optimal for in-band EUV emission. before reducing again at even higher intensity values (see inset in Fig. 4.2(b)).

Second, plasma is created using laser light of  $1-\mu m$  wavelength. Spectra for laser intensities within the range of  $(0.3-4.4) \times 10^{11}$  W/cm<sup>2</sup> are shown in Fig. 4.2(b). When compared to the  $2-\mu m$  drive-laser case the spectra show very similar shape, albeit at an apparent increased overall width. Again the same emission features of charge states Sn<sup>5+</sup>–Sn<sup>9+</sup> are visible at the lowest laser intensity but with somewhat less prominent emission features. This reduction in prominence is particularly noticeable for the peaks of charge states Sn<sup>6+</sup> and Sn<sup>7+</sup> (between 14 and 16 nm). Further the Sn<sup>9+</sup> peak at 14.2 nm is hardly visible (cf.  $0.2 \times 10^{11}$  W/cm<sup>2</sup> in the 2- $\mu$ m case). The SP rises until it reaches values of 9.7% around 2 × 10<sup>11</sup> W/cm<sup>2</sup> and subsequently decreases as the charge state balance becomes sub-optimal for emission of 13.5 nm light. The peak intensities used in this work agree well with previously published work, where the optimal SP was found at an intensity of



Figure 4.2: Spectra from tin droplet plasma observed at various intensities of the (a) 2- $\mu$ m beam (4.7 ns pulse duration, 106  $\mu$ m FWHM, 3 KTP crystals) and the (b) 1- $\mu$ m Nd:YAG beam (10 ns pulse duration, 86  $\mu$ m FWHM). The droplet size in both cases is 30  $\mu$ m. (c) Ratio of the intensities of 1- and 2- $\mu$ m drive laser beams needed to obtain spectra with similar spectral features. The data points represent the average intensity ratios from data taken with four different laser spot sizes of the 2- $\mu$ m laser beam of 65×88, 106, 152 and 194  $\mu$ m (FWHM), respectively. The error bars indicate the standard deviation per measurement. The red line represents the average over all data points and the shaded band the standard deviation of the average.

 $1.4 \times 10^{11}$  W/cm<sup>2</sup> using a temporally and spatially box-like laser profile to illuminate the tin droplets [84]. The higher intensity value found in this work is attributed to the fact that, because of their spatial extent, the droplets experience a slightly lower average intensity compared to the peak values stated.

To obtain the sought-for laser-intensity ratio  $I_{1\mu m}/I_{2\mu m}$ , each spectrum of the 2-µm laser case at intensity  $I_{2\mu m}$  is matched to a spectrum of the 1-µm case at intensity  $I_{1\mu\mu}$  for which the resemblance of the relative amplitudes and shape of spectral features is best matching. As the spectral features are characteristic of individual tin charge states [99, 100] this comparison provides access to the scaling of the plasma's charge state distribution (and hence temperature) with laser wavelength. For each match of laser intensities the ratio  $I_{1\mu m}/I_{2\mu m}$  is calculated and plotted as a function of  $I_{1\mu m}$  in Fig. 4.2(c). The data points represent the average of comparisons made for multiple spot-size conditions and for two droplet size conditions. In all cases spectra were compared to the ones taken with the 1-um wavelength laser beam size of 86 µm. More specifically, the comparison encompasses measurements with a 30-um-diameter droplet for 2-um case beam sizes of 65×88, 106×106, 152×152 and 194×194 μm and on a 19-μm-diameter droplet for the 65×88-µm beam. The red line shows the average  $I_{1\mu m}/I_{2\mu m} = 2.1(6)$  of all measurements with the standard deviation (distribution width and not the erroron-the-mean) of the mean value as red shaded area. The depicted uncertainty is the standard deviation of the mean.

#### Theory and discussion

The temperature of a plasma can be expressed analytically if the equation of state (EOS) is sufficiently well known. The required EOS parameters will however depend on the location in the plasma where the laser light is absorbed. Two cases can be distinguished [41]. Case I: absorption of laser light dominantly occurs close to the critical surface where the plasma's electron density equals the critical density ( $n_e \approx n_{\rm crit} \propto \lambda^{-2}$ ). This case is relevant for long wavelength laser light, e.g., from CO<sub>2</sub> lasers. Case II: absorption is already significant in the underdense corona where the electron density is lower than the critical electron density. For laser absorption of 1- and 2-µm beams, case II applies and the tin plasma temperature can be written as [41]

$$T \propto \left(\frac{1}{R\lambda^2}\right)^{-0.19} [I(1-\phi_r)]^{0.44},$$
 (4.1)

with laser wavelength  $\lambda$ , laser intensity *I*, radiative loss fraction  $\phi_r$  of the plasma and characteristic radius of the sonic surface *R*, defined as the contour at which the ion velocity equals the local sound velocity. The numerical values for the powers -0.19 and 0.44 originate from the EOS [41]. Differences in radiative losses of the plasmas are neglected in the following, as they may be small for similar density

and temperature plasmas. The sonic surface *R* is only slightly wavelength dependent and the small difference can be neglected. From Eq. (4.1), an intensity ratio  $I_i/I_j = (\lambda_j/\lambda_i)^{0.86}$  here  $I_{1\mu m}/I_{2\mu m} = 1.8$  is calculated for  $\lambda = 1$  and 2 µm plasmas exhibiting equal plasma temperatures. The predicted ratio of 1.8 agrees well with the experimental one of 2.1(6) and well approximates a scaling with  $\lambda^{-1}$ .

Alongside this analytical approach, the radiation hydrodynamic code RALEF-2D [17] is used to determine the laser intensity ratio yielding equivalent plasma temperatures. RALEF-2D was developed to simulate laser plasma interaction and solves the equations of fluid dynamics in two dimensions (assuming cylindrical symmetry around the laser beam propagation axis) while including necessary physical mechanisms such as laser absorption, thermal conduction and radiation transport. The latter is needed for accurate predictions of a strongly radiating plasma, which is true for the current case. An extensive set of simulations has been performed at conditions close to the experimental ones. A 30-um-diameter droplet is irradiated by temporally and spatially Gaussian beams. The 1- and  $2-\mu m$  beams have pulse durations of 10 and 4.3 ns (FWHM) and sizes of 80 and 100 µm (FWHM), respectively. Laser intensities in the range spanning  $10^{10}$ – $10^{12}$  W/cm<sup>2</sup> are simulated. The plasma's peak temperature is plotted in Fig. 4.3. For the given laser intensities the maximum temperature is consistently higher in the 2-µm case. We note that the different pulse durations (10 vs. 4.3 ns) have a minimal impact on temperature and density scales. The maximum temperatures are seen to follow Eq. (4.1) fitted as  $T[eV] = a \cdot \lambda^{0.38} [\mu m] \cdot I^{0.44} [10^{11} \text{ W/cm}^2]$ , where a common amplitude a = 43is determined by a global fit to all data. Eq. (4.1) captures the scaling of the peak plasma temperature over two decades in laser intensity.

Further shown in Fig. 4.3 are temperature and electron density lineouts along the laser axis away from the droplet at intensities relevant for the efficient emission of EUV light. The intensity of the 1- and 2-µm cases were chosen to have nearly identical peak electron temperature. This temperature strongly increases with distance from the droplet surface and peaks around 11 µm from the droplet surface before it reduces again at larger distances. The maximum temperature is obtained at a factor of 2.0 lower density in the 2-µm case. The point of highest temperature is much closer to the critical density in the 2-µm case indicating that the absorption of laser light occurs closer to critical density while the conditions for laser absorption of case II are still met. Following Ref. [41], and references therein, the scaling of the relevant plasma electron density with wavelength can also be approximated invoking a constant absorbed fraction of the laser light,  $k_L R$  = constant. Inserting the Kramers' absorption coefficient for laser radiation  $k_L$  we obtain [41, 101]

$$(R\lambda^2)\rho^2 \bar{z}^3 T^{-3/2} = \text{constant}, \tag{4.2}$$

with the mass density  $\rho$  and the plasma's average charge state  $\bar{z}$ . Considering that



Figure 4.3: Top: maximum temperature of a tin plasma for various laser intensities calculated with the two-dimensional-radiation transport code RALEF-2D. A 30-µm-diameter droplet is illuminated with temporally and spatially Gaussianshaped laser pulses of wavelengths 1 and 2 µm. Center: temperature and electron density lineout along the axis of the incoming laser beam. Bottom: frequencyintegrated local radiation field intensity  $I_{rad}$  of the plasma and its normalized derivative  $dI_{rad}$ . The radiation field intensity is calculated from Eq (4.3) using the density and temperature lineouts depicted in the center panel. For more detail see text.

mass density  $\rho$  and ion density  $n_i$  follow the ratio of electron density and average charge state  $\rho \propto n_i = n_e/\bar{z}$ , where  $\bar{z} \approx 22.5T^{0.6}$ [heV] (note that *T* is input here in units of 100 eV) [41], it becomes clear that the ratio of the electron densities lineouts displayed well approximates the ratio of mass density between the two laser wavelength cases. All other factors remaining constant in Eq. (4.2), a reciprocal scaling of mass density  $\rho$  and wavelength  $\lambda$  becomes directly apparent. The difference in mass density can thus be attributed to the difference in absorptivity of the laser radiation from Kramers' law [102]. This inversely proportional scaling of density with wavelength is the root cause of the observed intensity ratio.

The bottom panel of Fig. 4.3 shows the radiation field intensity  $I_{rad}$  and its normalized derivative  $dI_{rad}$ . The frequency-integrated radiation field intensity is calculated from

$$I_{\rm rad}(s) = I_0 e^{-\int_{s_0}^s \alpha(s')ds'} + \int_{s_0}^s \alpha(s')B(s')e^{-\int_{s'}^s \alpha(s'')ds''}ds'$$
(4.3)

with the Planck mean absorptivity  $\alpha_p[m^{-1}] = 3.3 \times 10^{-7} \cdot \rho[g/cm^3] \cdot T^{-1}[eV]$  using the temperature and electron density information in Fig. 4.3. For more information see Ref. [12]. The normalized derivatives  $dI_{rad}$  peak at 6.5 and 8  $\mu$ m distance from the droplet surface for the 1- and 2-µm cases, respectively. They show that the typical length scales of emission are similar in both wavelength cases. This finding is in line with the similarity in length scales and indeed profiles of plasma temperature and density (shown in the center panel of Fig. 4.3). The point of largest change in radiation field intensity is located slightly closer to the droplet surface than the point of maximum temperature. The significantly higher density more than compensates for the drop in temperature. The point of largest change in the radiation field intensity of the 1-µm-driven plasma occurs relatively far from the critical density, whereas in the 2- $\mu$ m-driven plasma this point lies close to the critical density, an observation explained by the distances between the respective maximum temperatures and critical densities. The radiation field intensity at large distances from the droplet surface is approximately a factor of two higher in the 1-µm case because of the factor of two higher (emitter) density compared to the 2-um case.

## 4.4 Scaling of optical depth

The scaling of mass density with drive laser wavelength  $\rho \propto \lambda^{-1}$  at similar length scales, as established by our simulations, indicates that the optical depth of the plasma, being a product of atomic opacity, mass density and path length, should scale similarly. If optical depth indeed reduces proportionally with drive laser wavelength, the step to a 2-µm laser system could be particularly beneficial. In the following, we perform an analysis of the optical depth associated with the EUV



Figure 4.4: Spectral emission from tin plasmas produced with 1- and  $2-\mu m$  laser wavelength for small and large droplet diameters at laser intensities of 2.4 and  $1.1 \times 10^{11} \text{ W/cm}^2$ , respectively.

spectra by varying plasma size following the work of Schupp *et al.* [89]. This is accomplished by irradiating droplets having diameters in the range  $16-51 \mu m$ .

# Scaling of peak optical depth with droplet size and drive laser wavelength: examples

In our experiments the droplet diameter is changed in controlled steps from 16– 51  $\mu$ m and a constant laser intensity is used for both laser wavelength cases. First, droplets are illuminated with 2- $\mu$ m laser light with an intensity of  $1.1 \times 10^{11}$  W/cm<sup>2</sup>, close to optimal SP. The spot size is 65×88  $\mu$ m. In Fig. 4.4 spectra for the smallest and largest droplet diameter are shown for both drive-laser cases. With increasing droplet diameter the main emission feature at 13.5 nm widens and more intense short-wavelength radiation is emitted relative to the 13.5-nm peak. Second, the same scan is repeated with 1- $\mu$ m laser light at 2.4 × 10<sup>11</sup> W/cm<sup>2</sup>, an intensity chosen based on the intensity ratio in Fig. 4.2(c). Again, the main emission feature at 13.5 nm widens with increasing droplet diameter and more intense short wavelength radiation is emitted relative to the 13.5-nm peak. For the 1- $\mu$ m driver these effects however are much stronger.

In the following, the spectra are analyzed regarding their optical depth similar to the analysis in Ref. [89]. The wavelength-dependent optical depth  $\tau_{\lambda} := \int \kappa_{\lambda} \rho dx$  is defined as the spatial integration over the product of the plasma's opacity  $\kappa_{\lambda}$  and mass density  $\rho$ . In the instructive case of a one-dimensional plasma [86] in local thermodynamic equilibrium (LTE), the spectral radiance is given by  $L_{\lambda} = B_{\lambda} (1 - e^{-\tau_{\lambda}})$ , where  $B_{\lambda}$  is the Planck blackbody spectral radiance. We note that our high-density, strongly collisional 1- and 2-µm-driven plasmas are reason-



Figure 4.5: Spectrum produced with 2-µm laser light (red line) compared to the radiation-transported reference spectrum for a peak optical depth value of  $\tau_p$  = 2.2 (gray line, barely distinguishable from the red line). Reference and 2-µm-driven spectra were both obtained using a droplet diameter of 30 µm. Also shown is a spectrum obtained using a 10-µm CO<sub>2</sub> laser that represents the case of small optical depth (reproduced from Ref. [13]).

ably well approximated by LTE [12]. At equal temperatures, and thus average charge state (recall  $\bar{z} \sim T^{0.6}$  [41]), this equation enables each measured spectrum  $\sim L_{\lambda,i}$  to be well approximated by any other spectrum  $\sim L_{\lambda,j}$  when taking into account the ratio of the corresponding peak optical depths  $a = \tau_{p,i}/\tau_{p,j}$  as a single parameter independent of wavelength (see Ref. [89] and the Appendix for further details). Subsequently, if any peak optical depth  $\tau_{p,j}$  is known in absolute terms, the optical depth of any other spectrum can be deduced. To be able to correct for systematic errors that could possibly occur for relatively low optical depth  $\tau \leq 1$  we have suitably modified the equation used in Ref. [89] as is detailed in the Appendix.

As a reference spectrum, the spectrum measured at 1-µm laser wavelength, 10ns pulse duration and 30-µm droplet size is chosen. The peak optical depth of this spectrum is determined by comparison of its 13.5-nm feature to opacity calculations in Ref. [12]. More specifically, radiation transport is applied to the opacity spectrum calculated in Ref. [12] for a here relevant mass density of  $\rho = 0.002 \text{ g/cm}^3$ and electron temperature of  $T_e = 32 \text{ eV}$ . The difference between radiation transported opacity spectrum and experimental spectrum is then minimized by changing the optical depth parameter  $\tau_p$  in a least-square fit routine. This procedure leads to an absolute peak optical depth of  $\tau_{0,p} = 4.5$  for our reference spectrum.

Using Eq. (4.7) the peak optical depth  $\tau_{i,p}$  of all spectra is fitted with respect to the reference spectrum. As expected, inserting the relative optical depth obtained from the fits into Eq. (4.6) leads to an excellent reproduction of the main emission feature, as is shown in Fig. 4.5 for a typical example spectrum (30-µm droplet with a 2-µm driver). A further reasonable reproduction of the 7–12 nm features is

established with the 2-µm driver outperforming the model spectrum with respect to the amount of radiation emitted out-of-band. Figure 4.5 also shows a spectrum from an industrial plasma produced by a 10-µm  $CO_2$  driver which represents the limiting case of low optical depth. The step from a 1-µm to a 2-µm driver clearly significantly enhances the spectrum.

# Scaling of peak optical depth with droplet size and drive laser wavelength: all results

Having demonstrated the ability of the model function to accurately reproduce spectra from a single reference spectrum, we show in Fig. 4.6(a) the fitted values for all spectra of the droplet size scans for 1- and 2-µm laser wavelength. In all cases the peak optical depth  $\tau_{i,p}$  appears to linearly increase with droplet diameter and to strongly depend on the laser wavelength. Indeed, the peak optical depth of the 2- $\mu$ m-driven plasma lies roughly a factor of 2 below that of the 1- $\mu$ m one at largest droplet size, which may be expected from the lower plasma density (cf. Section 4.3). However, the 1- $\mu$ m results were obtained with 10-ns-long pulses and are here compared to the results from approximately 5-ns-long, 2-um pulses, and optical depth is known to increase with pulse length [84, 89]. To provide a comparison on more equal footing, we further compare in Fig. 4.6(a) our results to previous data [89], obtained using a  $1-\mu m$  wavelength laser with a 5 ns temporally box-shaped laser pulse. One of these data sets is taken with a spatially flattop laser profile of 96-µm diameter [84, 89] while the other one is taken with a Gaussian laser beam profile of 66 µm FWHM which more closely resembles the experimental conditions for the 2-µm driver case. The spatial intensity distribution of the  $1-\mu m$  laser beam is seen to impact the effective optical depth (see also Ref. [84]). On comparison of the spectra for the 2- and  $1-\mu m$  cases at the most comparable temporal and spatial beam conditions, the clear reduction in peak optical depth parameter is maintained. This reduction, up to a factor 1.6 in optical depth, becomes more pronounced at larger droplet diameters. The small deviation from the factor of ~2 from the  $\rho \propto \lambda^{-1}$  scaling may originate from differences in plasma length scales, plasma temperature, or from the finite laser intensity gradient over the plasma length scale. Nevertheless, a very significant reduction in optical depth of up to 40% is demonstrated when using a  $2-\mu m$  laser to drive the plasma.

With peak optical depth being the pertinent scaling parameter of 1- and 2- $\mu$ mdriven tin plasmas the corresponding spectral purity of the emission spectrum is related to it in Fig. 4.6(b). All experimental SP values, calculated over the range of 5.5–25.5 nm, collapse onto the gray dashed curve obtained by calculating the SP of the radiation-transported reference spectrum. The 2- $\mu$ m case is slightly offset towards higher SP values because of the reduced emission in the 7–12 nm wavelength band compared to the radiation transported reference spectrum (cf. Fig. 4.5) that



Figure 4.6: (a) Dependency of peak optical depth  $\tau_{i,p}$  on droplet diameter for 5- and 10-ns laser pulse duration at 1-µm wavelength and for 4.3-ns pulse duration at 2-µm wavelength. Circles indicate Gaussian spatial laser profile and boxes indicate a homogeneous 'flattop' laser beam profile. Peak optical depth is fitted with respect to the spectrum obtained at 1-µm wavelength, 10-ns pulse duration and 30-µm droplet diameter with optical depth of  $\tau_{0,p} = 4.5$ . (b) Experimental values for spectral purity (SP) versus peak optical depth. The dashed line represents SP as calculated from the radiation-transported reference spectrum. The diamond symbol indicates the SP value of the radiation-transported reference spectrum for a peak optical depth value  $\tau_{i,p} = 0.4$ , obtained from comparison of the reference spectrum illustrated in Fig. 4.4.

is not captured by the model with the same accuracy as that of the main emission feature at 13.5 nm. This difference between model and experiment may point to a small overestimation of the optical depth of the 2-µm-laser-produced tin plasma, which would explain both the observed overestimation of the short-wavelength out-of-band emission by the model as well as the offset in Fig. 4.6(b). This small overestimation of the optical depth may in turn be due to a broader charge state distribution in our measurements of the 2-µm case caused by, e.g., laser intensity gradients or the slightly lower beam pointing stability compared to the 1-µm case. This observation leads us to expect an even lower optical depth in the 2-µm case and brings our scaling ratio even closer to the expected factor of 2 from the  $\lambda^{-1}$  scaling. More importantly, it indicates that there are further opportunities for narrowing the charge state distribution by providing a more homogeneous heating of the plasma in time and space. Such a narrowing of the charge state distribution around the optimum charge states Sn<sup>11+</sup>–Sn<sup>14+</sup> would lead to further improvements of SP and
thus CE.

### 4.5 Conclusions

In conclusion, the effects of optical depth, plasma density, and laser intensity on the emission spectra of a 2-um-LPP source of tin microdroplets are investigated. The results are compared to the case of a  $1-\mu$ m-driven plasma. It is found that the laser intensity required to maintain a common plasma temperature, scales approximately inversely with laser wavelength in going from a 1- to a 2-µm drive laser, a result that will help defining development goals for future 2-um drive lasers for LPP light sources. The reciprocal scaling with laser wavelength ( $\propto \lambda^{-1}$ ) has its origin in Kramers' law of inverse bremsstrahlung, the main laser absorption mechanism in the tin plasmas investigated. Because of its reduced plasma density, the optical depth of the 2-µm-driven plasma is significantly reduced, allowing for efficient out-coupling of 13.5-nm radiation from the plasma even at larger plasma sizes. In future experiments it will be of interest to use large, preformed targets and investigate the full CE potential of a  $2-\mu m$  source in a setting more similar to the current industrial one. Our results indicate that there are further opportunities for narrowing the charge state distribution by providing a more homogeneous heating of the plasma in time and space which would lead to further improvements of SP and thus CE. Looking further, it is of interest to experimentally investigate plasma generation using even longer-wavelength laser systems between 2 and  $10 \,\mu m$  to find the mid-infrared wavelength optimally suited to drive EUV light sources at 13.5 nm.

### 4.A Appendix

#### Radiation transport model

To determine peak optical depth in this work, the recorded spectra are analyzed in a manner similar to that presented in Ref. [89]. In the following, the method from Ref. [89] is first outlined briefly and is subsequently generalized for use with plasmas that are optically thin. The wavelength-dependent optical depth  $\tau_{\lambda} := \int \kappa_{\lambda} \rho dx$  is defined as the spatial integration over the product of the plasma's opacity  $\kappa_{\lambda}$  and mass density density  $\rho$ . The spectral radiance  $L_{\lambda}$  of an extended onedimensional plasma can be calculated by means of its optical depth as [86]

$$L_{\lambda} = S_{\lambda} \left( 1 - e^{-\tau_{\lambda}} \right). \tag{4.4}$$

In local thermodynamic equilibrium (LTE), where collisional processes drive atomic level populations, the source function  $S_{\lambda}$  equals the Planck blackbody function  $B_{\lambda}$ . Rearranging Eq. (4.4), the optical depth of the recorded plasma spectrum can be obtained from its relative spectral radiance  $L_{\lambda}/B_{\lambda}$ 

$$\tau_{\lambda} = -\ln\left(1 - \frac{L_{\lambda}}{B_{\lambda}}\right). \tag{4.5}$$

The optical depths of two plasmas of similar temperatures, but with modestly different densities and length scales, may differ (in first approximation) only by a single wavelength-independent multiplicative factor  $a_i$ , relating the plasmas' optical depths via  $\tau_{\lambda,i} = a_i \tau_{\lambda,0}$ . Here  $\tau_0$  and  $\tau_i$  are the two wavelength-dependent optical depths of the reference spectrum and any other spectrum *i*, respectively. The relative spectral radiances of these two plasmas can be related to each other via Eq. (4.5)

$$\frac{L_{\lambda,i}}{B_{\lambda}} = 1 - \left(1 - \frac{L_{\lambda,0}}{B_{\lambda}}\right)^{\tau_i/\tau_0}.$$
(4.6)

In order to apply Eq. (4.6) to the spectra measured, the relative spectral radiance of the spectra must be known. To obtain the relative spectral radiance, the ratio of observed spectrum  $O_{\lambda}$  (meaning the spectrum as recorded with the spectrometer) and blackbody function is normalized to the peak value at 13.5-nm wavelength (subscript *p*) by replacing *L* with  $\tilde{L}_{\lambda} = O_{\lambda}B_p/O_p$ . The normalized ratio  $\tilde{L}_{\lambda}/B_{\lambda}$  is then multiplied by the amplitude factor  $1 - e^{-\tau_p}$  obtained from Eq. (4.5)

$$\frac{\tilde{L}_{\lambda,i}}{B_{\lambda}} = \frac{1 - \left(1 - \frac{\tilde{L}_{\lambda,0}}{B_{\lambda}} (1 - e^{-\tau_{0,p}})\right)^{\tau_{i,p}/\tau_{0,p}}}{1 - e^{-\tau_{i,p}}}.$$
(4.7)

Note that the wavelength-dependent optical depth values  $(\tau_{0,\lambda})$  from Eq. (4.6) have been exchanged by their peak values  $(\tau_{0,p})$ . This generalized equation allows for determination of peak optical depth in optically thin plasmas in LTE if the peak optical depth of one of the spectra is known. In the current analysis the use of Eq. (4.7) results in optical depth values that are mostly very similar, but some of which are up to 25% lower for the smallest optical depths cases ( $\tau \sim 2$ ), than when using Eq. (4.6). Using Eq. (4.7) the peak optical depths  $\tau_{i,p}$  of all spectra are fitted with respect to a reference spectrum of known peak optical depth (see main text).

# 5 | Characterization of angularly resolved EUV emission from 2-μm-wavelength laser-driven Sn plasma using preformed liquid disk targets

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To be submitted





# 5.1 Introduction

Experiment



# 5.2 Experiment









Characterization of angularly resolved EUV emission...



### 5.3 EUV generation using $2-\mu m$ light on preformed targets



### 5.3.1 Target diameter





Figure 5.2: Caption on the following page.





Characterization of angularly resolved EUV emission...



### 5.3.2 Laser intensity



### 5.3.3 Pulse duration



Characterization of angularly resolved EUV emission...





### 5.4 EUV generation using 1- and 2- $\mu$ m laser light







Characterization of angularly resolved EUV emission...



### 5.5 Conclusions



# References

- <sup>1</sup>R. G. Arns, "The other transistor: early history of the metal-oxide semiconductor field-effect transistor", Eng. Sci. Educ. J. 7, 233–240 (1998).
- <sup>2</sup>L. J. Edgar, *Method and apparatus for controlling electric currents*, US Patent 1,745,175, Jan. 1930.
- <sup>3</sup>J. Bardeen and W. H. Brattain, "The transistor, a semi-conductor triode", Phys. Rev. **74**, 230–231 (1948).
- <sup>4</sup>C.-T. Sah, "Evolution of the MOS transistor—from conception to VLSI", Proc. IEEE **76**, 1280–1326 (1988).
- <sup>5</sup>G. E. Moore, "Progress in digital integrated electronics", Proc. IEDM Tech. Dig. **11**, 11–13 (1975).
- <sup>6</sup>G. E. Moore, "Cramming More Components Onto Integrated Circuits", Proc. IEEE **86**, 82–85 (1998).
- <sup>7</sup>T. N. Theis and H.-S. Philip Wong, "The end of moore's law: A new beginning for information technology", Comput. Sci. Eng. **19**, 41–50 (2017).
- <sup>8</sup>I. Fomenkov, *EUV Source for Lithography in HVM: performance and prospects*, EUV Source Workshop 2019, presented: November 5, 2019.
- <sup>9</sup>C. De Young, *EUV: Enabling cost efficiency, tech innovation and future industry growth*, BAML 2019 APAC TMT Conference, presented: March 20, 2019.
- <sup>10</sup>S. Bajt, J. B. Alameda, T. W. Barbee Jr., W. M. Clift, J. A. Folta, B. B. Kaufmann, and E. A. Spiller, "Improved reflectance and stability of Mo/Si multilayers", Opt. Eng. **41**, 1797–1804 (2002).
- <sup>11</sup>M. Purvis, I. V. Fomenkov, A. A. Schafgans, M. Vargas, S. Rich, Y. Tao, S. I. Rokitski, M. Mulder, E. Buurman, M. Kats, J. Stewart, A. D. LaForge, C. Rajyaguru, G. Vaschenko, A. I. Ershov, R. J. Rafac, M. Abraham, D. C. Brandt, and D. J. Brown, "Industrialization of a robust EUV source for high-volume manufacturing and power scaling beyond 250 W", in EUV Lithography IX, Vol. 10583 (SPIE, 2018), 1058327.

- <sup>12</sup>F. Torretti, J. Sheil, R. Schupp, M. M. Basko, M. Bayraktar, R. A. Meijer, S. Witte, W. Ubachs, R. Hoekstra, O. O. Versolato, A. J. Neukirch, and J. Colgan, "Prominent radiative contributions from multiply-excited states in laser-produced tin plasma for nanolithography", Nat. Commun. **11**, 2334 (2020).
- <sup>13</sup>M. van de Kerkhof, F. Liu, M. Meeuwissen, X. Zhang, M. Bayraktar, R. de Kruif, and N. Davydova, "High-power EUV lithography: spectral purity and imaging performance", J. Micro Nanolithogr. MEMS MOEMS **19**, 033801 (2020).
- <sup>14</sup>M. M. Marinak, G. D. Kerbel, N. A. Gentile, O. Jones, D. Munro, S. Pollaine, T. R. Dittrich, and S. W. Haan, "Three-dimensional HYDRA simulations of National Ignition Facility targets", Phys. Plasmas 8, 2275–2280 (2001).
- <sup>15</sup>S. Langer, H. Scott, T. Galvin, E. Link, B. Regan, and C. Siders, *Simulations of Laser Driven EUV Sources the Impact of Laser Wavelength*, EUVL Workshop 2020, presented: June 11, 2020.
- <sup>16</sup>E. Sistrunk, D. A. Alessi, A. Bayramian, K. Chesnut, A. Erlandson, T. C. Galvin, D. Gibson, H. Nguyen, B. Reagan, K. Schaffers, C. W. Siders, T. Spinka, and C. Haefner, "Laser Technology Development for High Peak Power Lasers Achieving Kilowatt Average Power and Beyond", in *Short-pulse High-energy Lasers and Ultrafast Optical Technologies*, Vol. 11034, edited by P. Bakule and C. L. Haefner (SPIE, 2019), 1–8.
- <sup>17</sup>M. M. Basko, J. Maruhn, and A. Tauschwitz, "Development of a 2D radiationhydrodynamics code RALEF for laser plasma simulations", GSI report 1, 410 (2010).
- <sup>18</sup>G. O'Sullivan, B. Li, R. D'Arcy, P. Dunne, P. Hayden, D. Kilbane, T. McCormack, H. Ohashi, F. O'Reilly, P. Sheridan, E. Sokell, C. Suzuki, and T. Higashiguchi, "Spectroscopy of highly charged ions and its relevance to EUV and soft x-ray source development", J. Phys. B: At. Mol. Opt. Phys. **48**, 144025 (2015).
- <sup>19</sup>V. I. Azarov and Y. N. Joshi, "Analysis of the  $4d^7$ – $4d^65p$  transition array of the eighth spectrum of tin: Sn VIII", J. Phys. B: At. Mol. Opt. Phys. **26**, 3495–3514 (1993).
- <sup>20</sup>W. Svendsen and G. O'Sullivan, "Statistics and characteristics of xuv transition arrays from laser-produced plasmas of the elements tin through iodine", Phys. Rev. A 50, 3710–3718 (1994).
- <sup>21</sup>S. S. Churilov and A. N. Ryabtsev, "Analyses of the Sn IX–Sn XII spectra in the EUV region", Phys. Scr. 73, 614–619 (2006).
- <sup>22</sup>S. S. Churilov and A. N. Ryabtsev, "Analysis of the  $4p^64d^7 (4p^64d^64f + 4p^54d^8)$  transitions in the Sn VIII spectrum", Opt. Spectrosc. **100**, 660–666 (2006).
- <sup>23</sup>S. S. Churilov and A. N. Ryabtsev, "Analysis of the spectra of In XII–XIV and Sn XIII–XV in the far-VUV region", Opt. Spectrosc. **101**, 169–178 (2006).

- <sup>24</sup>A. N. Ryabtsev, É. Ya. Kononov, and S. S. Churilov, "Spectra of rubidium-like Pd X–Sn XIV ions", Opt. Spectrosc. **105**, 844–850 (2008).
- <sup>25</sup>I. Yu. Tolstikhina, S. S. Churilov, A. N. Ryabtsev, and K. N. Koshelev, "Atomic tin data", in *EUV sources for lithography*, edited by V. Bakshi (SPIE press Bellingham, Washington, 2006) Chap. 4, 113–148.
- <sup>26</sup>R. D'Arcy, H. Ohashi, S. Suda, H. Tanuma, S. Fujioka, H. Nishimura, K. Nishihara, C. Suzuki, T. Kato, F. Koike, J. White, and G. O'Sullivan, "Transitions and the effects of configuration interaction in the spectra of Sn XV–Sn XVIII", Phys. Rev. A **79**, 042509 (2009).
- <sup>27</sup>H. Ohashi, S. Suda, H. Tanuma, S. Fujioka, H. Nishimura, A. Sasaki, and K. Nishihara, "EUV emission spectra in collisions of multiply charged Sn ions with He and Xe", J. Phys. B: At. Mol. Opt. Phys. **43**, 065204 (2010).
- <sup>28</sup>A. Windberger, F. Torretti, A. Borschevsky, A. Ryabtsev, S. Dobrodey, H. Bekker, E. Eliav, U. Kaldor, W. Ubachs, R. Hoekstra, J. R. Crespo López-Urrutia, and O. O. Versolato, "Analysis of the fine structure of Sn<sup>11+</sup>–Sn<sup>14+</sup> ions by optical spectroscopy in an electron-beam ion trap", Phys. Rev. A **94**, 012506 (2016).
- <sup>29</sup>J. Colgan, D. P. Kilcrease, J. Abdallah, M. E. Sherrill, C. J. Fontes, P. Hakel, and G. S. J. Armstrong, "Atomic structure considerations for the low-temperature opacity of Sn", High Energy Density Phys. **23**, 133–137 (2017).
- <sup>30</sup>F. Torretti, A. Windberger, A. Ryabtsev, S. Dobrodey, H. Bekker, W. Ubachs, R. Hoekstra, E. V. Kahl, J. C. Berengut, J. R. Crespo López-Urrutia, and O. O. Versolato, "Optical spectroscopy of complex open-4*d*-shell ions Sn<sup>7+</sup>–Sn<sup>10+</sup>", Phys. Rev. A **95**, 042503 (2017).
- <sup>31</sup>V. Y. Banine, K. N. Koshelev, and G. H. P. M. Swinkels, "Physical processes in EUV sources for microlithography", J. Phys. D: Appl. Phys. **44**, 253001 (2011).
- <sup>32</sup>J. Benschop, V. Banine, S. Lok, and E. Loopstra, "Extreme ultraviolet lithography: Status and prospects", J. Vac. Sci. Technol. B **26**, 2204–2007 (2008).
- <sup>33</sup>Y. Kawasuji, K. M. Nowak, T. Hori, T. Okamoto, H. Tanaka, Y. Watanabe, T. Abe, T. Kodama, Y. Shiraishi, H. Nakarai, T. Yamazaki, S. Okazaki, T. Saitou, H. Mizoguchi, and Y. Shiraishi, "Key components technology update of the 250W high-power LPP-EUV light source", in SPIE Advanced Lithography, Vol. 10143 (SPIE, 2017), 101432G.
- <sup>34</sup>I. Fomenkov, D. Brandt, A. Ershov, A. Schafgans, Y. Tao, G. Vaschenko, S. Rokitski, M. Kats, M. Vargas, M. Purvis, R. Rafac, B. La Fontaine, S. De Dea, A. LaForge, J. Stewart, S. Chang, M. Graham, D. Riggs, T. Taylor, M. Abraham, and D. Brown, "Light sources for high-volume manufacturing EUV lithography: technology, performance, and power scaling", Adv. Opt. Techn. 6, 173–186 (2017).

- <sup>35</sup>D. Kurilovich, A. L. Klein, F. Torretti, A. Lassise, R. Hoekstra, W. Ubachs, H. Gelderblom, and O. O. Versolato, "Plasma propulsion of a metallic microdroplet and its deformation upon laser impact", Phys. Rev. Appl. 6, 014018 (2016).
- <sup>36</sup>D. Kurilovich, T. de Faria Pinto, F. Torretti, R. Schupp, J. Scheers, A. S. Stodolna, H. Gelderblom, K. S. E. Eikema, S. Witte, W. Ubachs, R. Hoekstra, and O. O. Versolato, "Expansion Dynamics after Laser-Induced Cavitation in Liquid Tin Microdroplets", Phys. Rev. Applied **10**, 054005 (2018).
- <sup>37</sup>M. S. Krivokorytov, A. Yu. Vinokhodov, Yu. V. Sidelnikov, V. M. Krivtsun, V. O. Kompanets, A. A. Lash, K. N. Koshelev, and V. V. Medvedev, "Cavitation and spallation in liquid metal droplets produced by subpicosecond pulsed laser radiation", Phys. Rev. E **95**, 031101 (2017).
- <sup>38</sup>S. Yu. Grigoryev, B. V. Lakatosh, M. S. Krivokorytov, V. V. Zhakhovsky, S. A. Dyachkov, D. K. Ilnitsky, K. P. Migdal, N. A. Inogamov, A. Yu. Vinokhodov, V. O. Kompanets, Yu. V. Sidelnikov, V. M. Krivtsun, K. N. Koshelev, and V. V. Medvedev, "Expansion and Fragmentation of a Liquid-Metal Droplet by a Short Laser Pulse", Phys. Rev. Appl. **10**, 064009 (2018).
- <sup>39</sup>V. Bakshi, ed., *EUV Lithography*, 2nd Edition (SPIE press Bellingham, Washington, 2018).
- <sup>40</sup>Q. Huang, V. Medvedev, R. van de Kruijs, A. Yakshin, E. Louis, and F. Bijkerk, "Spectral tailoring of nanoscale EUV and soft x-ray multilayer optics", Appl. Phys. Rev. **4**, 011104 (2017).
- <sup>41</sup>M. M. Basko, V. G. Novikov, and A. S. Grushin, "On the structure of quasistationary laser ablation fronts in strongly radiating plasmas", Phys. Plasmas **22**, 053111 (2015).
- <sup>42</sup>P. Mora, "Theoretical model of absorption of laser light by a plasma", Phys. Fluids **25**, 1051–1056 (1982).
- <sup>43</sup>T. W. Johnston and J. M. Dawson, "Correct values for high-frequency power absorption by inverse bremsstrahlung in plasmas", Phys. Fluids **16**, 722–722 (1973).
- <sup>44</sup>S. Fujioka, H. Nishimura, K. Nishihara, A. Sasaki, A. Sunahara, T. Okuno, N. Ueda, T. Ando, Y. Tao, Y. Shimada, K. Hashimoto, M. Yamaura, K. Shigemori, M. Nakai, K. Nagai, T. Norimatsu, T. Nishikawa, N. Miyanaga, Y. Izawa, and K. Mima, "Opacity Effect on Extreme Ultraviolet Radiation from Laser-Produced Tin Plasmas", Phys. Rev. Lett. **95**, 235004 (2005).
- <sup>45</sup>H. Tanaka, A. Matsumoto, K. Akinaga, A. Takahashi, and T. Okada, "Comparative study on emission characteristics of extreme ultraviolet radiation from CO<sub>2</sub> and Nd:YAG laser-produced tin plasmas", Appl. Phys. Lett. **87**, 041503 (2005).

- <sup>46</sup>P. Hayden, A. Cummings, N. Murphy, G. O'Sullivan, P. Sheridan, J. White, and P. Dunne, "13.5 nm extreme ultraviolet emission from tin based laser produced plasma sources", J. Appl. Phys. **99**, 093302 (2006).
- <sup>47</sup>J. White, P. Dunne, P. Hayden, F. O'Reilly, and G. O'Sullivan, "Optimizing 13.5 nm laser-produced tin plasma emission as a function of laser wavelength", Appl. Phys. Lett. **90**, 181502 (2007).
- <sup>48</sup>R. C. Spitzer, T. J. Orzechowski, D. W. Phillion, R. L. Kauffman, and C. Cerjan, "Conversion efficiencies from laser-produced plasmas in the extreme ultraviolet regime", J. Appl. Phys. **79**, 2251–2258 (1996).
- <sup>49</sup>T. Ando, S. Fujioka, H. Nishimura, N. Ueda, Y. Yasuda, K. Nagai, T. Norimatsu, M. Murakami, K. Nishihara, N. Miyanaga, Y. Izawa, K. Mima, and A. Sunahara, "Optimum laser pulse duration for efficient extreme ultraviolet light generation from laser-produced tin plasmas", Appl. Phys. Lett. **89**, 151501 (2006).
- <sup>50</sup>Y. Tao, S. S. Harilal, M. S. Tillack, K. L. Sequoia, B. O'Shay, and F. Najmabadi, "Effect of focal spot size on in-band 13.5 nm extreme ultraviolet emission from laser-produced Sn plasma", Opt. Lett. **31**, 2492–2494 (2006).
- <sup>51</sup>S. A. George, W. T. Silfvast, K. Takenoshita, R. T. Bernath, C.-S. Koay, G. Shimkaveg, and M. C. Richardson, "Comparative extreme ultraviolet emission measurements for lithium and tin laser plasmas", Opt. Lett. **32**, 997–999 (2007).
- <sup>52</sup>O. Morris, F. O'Reilly, P. Dunne, and P. Hayden, "Angular emission and selfabsorption studies of a tin laser produced plasma extreme ultraviolet source between 10 and 18 nm", Appl. Phys. Lett. **92**, 231503 (2008).
- <sup>53</sup>K. L. Sequoia, "Extreme-ultraviolet radiation transport in small scale length laserproduced tin plasmas", PhD thesis (UC San Diego, 2009).
- <sup>54</sup>Y. Tao, Y. Ueno, S. Yuspeh, R. Burdt, M. S. Tillack, and F. Najmabadi, "Investigation on the interaction of long duration Nd:YAG laser pulse with Sn plasma for an EUV metrology source", in EUV Lithography II, Vol. 7969 (SPIE, 2011), 796930.
- <sup>55</sup>A. Roy, S. Murtaza Hassan, S. S. Harilal, A. Endo, T. Mocek, and A. Hassanein, "Extreme ultraviolet emission and confinement of tin plasmas in the presence of a magnetic field", Phys. Plasmas **21**, 053106 (2014).
- <sup>56</sup>A. Roy, G. Arai, H. Hara, T. Higashiguchi, H. Ohashi, A. Sunahara, B. Li, P. Dunne, G. O'Sullivan, T. Miura, T. Mocek, and A. Endo, "Evolution of laser-produced Sn extreme ultraviolet source diameter for high-brightness source", Appl. Phys. Lett. **105**, 074103 (2014).
- <sup>57</sup>M. G. Su, Q. Min, S. Q. Cao, D. X. Sun, P. Hayden, G. O'Sullivan, and C. Z. Dong, "Evolution analysis of EUV radiation from laser-produced tin plasmas based on a radiation hydrodynamics model", Sci. Rep. 7, 45212 (2017).

- <sup>58</sup>S. Fujioka, H. Nishimura, K. Nishihara, M. Murakami, Y.-G. Kang, Q. Gu, K. Nagai, T. Norimatsu, N. Miyanaga, Y. Izawa, and K. Mima, "Properties of ion debris emitted from laser-produced mass-limited tin plasmas for extreme ultraviolet light source applications", Appl. Phys. Lett. 87, 241503 (2005).
- <sup>59</sup>Y. Shimada, H. Nishimura, M. Nakai, K. Hashimoto, M. Yamaura, Y. Tao, K. Shigemori, T. Okuno, K. Nishihara, T. Kawamura, A. Sunahara, T. Nishikawa, A. Sasaki, K. Nagai, T. Norimatsu, S. Fujioka, S. Uchida, N. Miyanaga, Y. Izawa, and C. Yamanaka, "Characterization of extreme ultraviolet emission from laser-produced spherical tin plasma generated with multiple laser beams", Appl. Phys. Lett. 86, 051501 (2005).
- <sup>60</sup>S. Yuspeh, K. L. Sequoia, Y. Tao, M. S. Tillack, R. Burdt, and F. Najmabadi, "Optimization of the size ratio of Sn sphere and laser focal spot for an extreme ultraviolet light source", Appl. Phys. Lett. **93**, 221503 (2008).
- <sup>61</sup>S. Yuspeh, Y. Tao, R. A. Burdt, M. S. Tillack, Y. Ueno, and F. Najmabadi, "Dynamics of laser-produced Sn microplasma for a high-brightness extreme ultraviolet light source", Appl. Phys. Lett. **98**, 201501 (2011).
- <sup>62</sup>J. R. Freeman, S. S. Harilal, B. Verhoff, A. Hassanein, and B. Rice, "Laser wavelength dependence on angular emission dynamics of Nd:YAG laser-produced Sn plasmas", Plasma Sources Sci. Technol. **21**, 055003 (2012).
- <sup>63</sup>A. Yu. Vinokhodov, M. S. Krivokorytov, Yu. V. Sidelnikov, V. M. Krivtsun, V. V. Medvedev, and K. N. Koshelev, "Droplet-based, high-brightness extreme ultraviolet laser plasma source for metrology", J. Appl. Phys. **120**, 163304 (2016).
- <sup>64</sup>A. Z. Giovannini and R. S. Abhari, "Three-dimensional extreme ultraviolet emission from a droplet-based laser-produced plasma", J. Appl. Phys. **114**, 033303 (2013).
- <sup>65</sup>A. Z. Giovannini and R. S. Abhari, "Effects of the dynamics of droplet-based laserproduced plasma on angular extreme ultraviolet emission profile", Appl. Phys. Lett. **104**, 194104 (2014).
- <sup>66</sup>H. Chen, X. Wang, L. Duan, H. Lan, Z. Chen, D. Zuo, and P. Lu, "Angular distribution of ions and extreme ultraviolet emission in laser-produced tin droplet plasma", J. Appl. Phys. **117**, 193302 (2015).
- <sup>67</sup>S. J. Goh, H. J. M. Bastiaens, B. Vratzov, Q. Huang, F. Bijkerk, and K. J. Boller, "Fabrication and characterization of free-standing, high-line-density transmission gratings for the vacuum UV to soft X-ray range", Opt. Express 23, 4421– 4434 (2015).
- <sup>68</sup>M. Bayraktar, H. M. Bastiaens, C. Bruineman, B. Vratzov, and F. Bijkerk, "Broadband transmission grating spectrometer for measuring the emission spectrum of EUV sources", NEVAC blad 54, 14–19 (2016).

- <sup>69</sup>M. M. Basko, "On the maximum conversion efficiency into the 13.5-nm extreme ultraviolet emission under a steady-state laser ablation of tin microspheres", Phys. Plasmas 23, 083114 (2016).
- <sup>70</sup>D. Kurilovich, M. M. Basko, D. A. Kim, F. Torretti, R. Schupp, J. C. Visschers, J. Scheers, R. Hoekstra, W. Ubachs, and O. O. Versolato, "Power-law scaling of plasma pressure on laser-ablated tin microdroplets", Phys. Plasmas 25, 012709 (2018).
- <sup>71</sup>B. O'Shay, F. Najmabadi, S. S. Harilal, and M. S. Tillack, "Nanosecond spectroscopy of expanding laser-produced tin plasma", in J. Phys. Conf. Ser. Vol. 59, 1 (2007), 165.
- <sup>72</sup>M. S. Tillack, K. L. Sequoia, and Y. Tao, "Geometric effects on EUV emissions in spherical and planar targets", in J. Phys. Conf. Ser. Vol. 112, 4 (IOP Publishing, 2008), 042060.
- <sup>73</sup>R. A. Meijer, A. S. Stodolna, K. S. E. Eikema, and S. Witte, "High-energy Nd:YAG laser system with arbitrary sub-nanosecond pulse shaping capability", Opt. Lett. **42**, 2758–2761 (2017).
- <sup>74</sup>A. Kramida, Y. Ralchenko, J. Reader, and and NIST ASD Team, NIST Atomic Spectra Database (ver. 5.3), [Online]. Available: http://physics.nist. gov/asd [2016, February 2]. National Institute of Standards and Technology, Gaithersburg, MD., 2015.
- <sup>75</sup>M. Yamaura, S. Uchida, A. Sunahara, Y. Shimada, H. Nishimura, S. Fujioka, T. Okuno, K. Hashimoto, K. Nagai, T. Norimatsu, K. Nishihara, N. Miyanga, Y. Izawa, and C. Yamanaka, "Characterization of extreme ultraviolet emission using the fourth harmonic of a Nd:YAG laser", Appl. Phys. Lett. **86**, 181107 (2005).
- <sup>76</sup>F. Torretti, R. Schupp, D. Kurilovich, A. Bayerle, J. Scheers, W. Ubachs, R. Hoekstra, and O. O. Versolato, "Short-wavelength out-of-band EUV emission from Sn laser-produced plasma", J. Phys. B: At. Mol. Opt. Phys. **51**, 045005 (2018).
- <sup>77</sup>C. R. Phipps Jr., T. P. Turner, R. F. Harrison, G. W. York, W. Z. Osborne, G. K. Anderson, X. F. Corlis, L. C. Haynes, H. S. Steele, K. C. Spicochi, and T. R. King, "Impulse coupling to targets in vacuum by KrF, HF, and CO<sub>2</sub> single-pulse lasers", J. Appl. Phys. **64**, 1083–1096 (1988).
- <sup>78</sup>M. Murakami, J. Meyer-ter-Vehn, and R. Ramis, "Thermal X-Ray Emission from Ion-Beam-Heated Matter", J. Xray Sci. Technol. 2, 127–148 (1990).
- <sup>79</sup>M. Murakami, S. Fujioka, H. Nishimura, T. Ando, N. Ueda, Y. Shimada, and M. Yamaura, "Conversion efficiency of extreme ultraviolet radiation in laserproduced plasmas", Phys. Plasmas **13**, 033107 (2006).

- <sup>80</sup>O. O. Versolato, "Physics of laser-driven tin plasma sources of EUV radiation for nanolithography", Plasma Sources Sci. Technol. 28, 083001 (2019).
- <sup>81</sup>S. K. Moore, "EUV lithography finally ready for fabs", IEEE Spectrum **55**, 46–48 (2018).
- <sup>82</sup>A. A. Schafgans, D. J. Brown, I. V. Fomenkov, R. Sandstrom, A. Ershov, G. Vaschenko, R. Rafac, M. Purvis, S. Rokitski, Y. Tao, D. J. Riggs, W. J. Dunstan, M. Graham, N. R. Farrar, D. C. Brandt, N. Böwering, A. Pirati, N. Harned, C. Wagner, H. Meiling, and R. Kool, "Performance optimization of MOPA pre-pulse LPP light source", in EUV Lithography VI, Vol. 9422 (SPIE, 2015), 94220B.
- <sup>83</sup>M. A. Purvis, A. Schafgans, D. J. W. Brown, I. Fomenkov, R. Rafac, J. Brown, Y. Tao, S. Rokitski, M. Abraham, M. Vargas, S. Rich, T. Taylor, D. Brandt, A. Pirati, A. Fisher, H. Scott, A. Koniges, D. Eder, S. Wilks, A. Link, and S. Langer, "Advancements in predictive plasma formation modeling", in EUV Lithography VII, Vol. 9776 (SPIE, 2016), 97760K.
- <sup>84</sup>R. Schupp, F. Torretti, R. A. Meijer, M. Bayraktar, J. Scheers, D. Kurilovich, A. Bayerle, K. S. E. Eikema, S. Witte, W. Ubachs, R. Hoekstra and O. O. Versolato, "Efficient generation of extreme ultraviolet light from Nd: YAG-driven microdroplet-tin plasma", Phys. Rev. Appl. **12**, 014010 (2019).
- <sup>85</sup>D. Colombant and G. F. Tonon, "X-ray emission in laser-produced plasmas", J. Appl. Phys. 44, 3524–3537 (1973).
- <sup>86</sup>V. Bakshi, *EUV sources for lithography*, Vol. 149 (SPIE press Bellingham, Washington, 2006).
- <sup>87</sup>A. Hassanein, V. A. Sizyuk, T. S. Sizyuk, and S. S. Harilal, "Effects of plasma spatial profile on conversion efficiency of laser-produced plasma sources for EUV lithography", J. Micro/Nanolithogr. MEMS MOEMS 8, 041503 (2009).
- <sup>88</sup>A. Hassanein, T. Sizyuk, V. Sizyuk, and S. S. Harilal, "Combined effects of prepulsing and target geometry on efficient EUV production from laser produced plasma experiments and modeling", in EUV Lithography II, Vol. 7969 (SPIE, 2011), 79690D.
- <sup>89</sup>R. Schupp, F. Torretti, R. A. Meijer, M. Bayraktar, J. Sheil, J. Scheers, D. Kurilovich, A. Bayerle, A. A. Schafgans, M. Purvis, K. S. E. Eikema, S. Witte, W. Ubachs, R. Hoekstra, and O. O. Versolato, "Radiation transport and scaling of optical depth in Nd:YAG laser-produced microdroplet-tin plasma", Appl. Phys. Lett. **115**, 124101 (2019).
- <sup>90</sup>S. S. Harilal, T. Sizyuk, A. Hassanein, D. Campos, P. Hough, and V. Sizyuk, "The effect of excitation wavelength on dynamics of laser-produced tin plasma", J. Appl. Phys. **109**, 063306 (2011).

- <sup>91</sup>C. W. Siders, A. C. Erlandson, T. C. Galvin, H. Frank, S. Langer, B. A. Reagan, H. Scott, E. F. Sistrunk, and T. M. Spinka, *Efficient high power laser drivers for next-generation High Power EUV sources*, EUV Source Workshop 2019, presented: November 6, 2019.
- <sup>92</sup>G. Arisholm, Ø. Nordseth, and G. Rustad, "Optical parametric master oscillator and power amplifier for efficient conversion of high-energy pulses with high beam quality", Opt. Express **12**, 4189–4197 (2004).
- <sup>93</sup>J. Scheers, C. Shah, A. Ryabtsev, H. Bekker, F. Torretti, J. Sheil, D. A. Czapski, J. C. Berengut, W. Ubachs, J. R. Crespo López-Urrutia, R. Hoekstra, and O. O. Versolato, "EUV spectroscopy of highly charged Sn<sup>13+</sup>–Sn<sup>15+</sup> ions in an electronbeam ion trap", Phys. Rev. A **101**, 062511 (2020).
- <sup>94</sup>K. L. Sequoia, Y. Tao, S. Yuspeh, R. Burdt, and M. S. Tillack, "Two dimensional expansion effects on angular distribution of 13.5 nm in-band extreme ultraviolet emission from laser-produced Sn plasma", Appl. Phys. Lett. **92**, 221505 (2008).
- <sup>95</sup>H. Chen, H. Lan, Z.-Q. Chen, L.-N. Liu, T. Wu, D.-L. Zuo, P.-X. Lu, and X.-B. Wang, "Experimental study on laser produced tin droplet plasma extreme ultraviolet light source", Acta Phys. Sin. 64, 075202 (2015).
- <sup>96</sup>J. P. Apruzese, J. Davis, K. G. Whitney, J. W. Thornhill, P. C. Kepple, R. W. Clark, C. Deeney, C. A. Coverdale, and T. W. L. Sanford, "The physics of radiation transport in dense plasmas", Phys. Plasmas 9, 2411–2419 (2002).
- <sup>97</sup>A. Sasaki, A. Sunahara, K. Nishihara, T. Nishikawa, K. Fujima, T. Kagawa, F. Koike, and H. Tanuma, "Atomic modeling of the plasma EUV sources", High Energy Density Phys. **3**, 250–255 (2007).
- <sup>98</sup>C. N. Danson, C. Haefner, J. Bromage, T. Butcher, J.-C. F. Chanteloup, E. A. Chowdhury, A. Galvanauskas, L. A. Gizzi, J. Hein, D. I. Hillier, N. W. Hopps, Y. Kato, E. A. Khazanov, R. Kodama, G. Korn, R. Li, Y. Li, J. Limpert, J. Ma, N. Chang-hee, D. Neely, D. Papadopoulos, R. R. Penman, L. Qian, J. J. Rocca, A. A. Shaykin, C. W. Siders, C. Spindloe, S. Szatmári, R. M. G. M. Trines, J. Zhu, P. Zhu, and J. D. Zuegel, "Petawatt and exawatt class lasers worldwide", High Power Laser Sci. Eng. 7 (2019).
- <sup>99</sup>F. Torretti, F. Liu, M. Bayraktar, J. Scheers, Z. Bouza, W. Ubachs, R. Hoekstra, and O. O. Versolato, "Spectral characterization of an industrial EUV light source for nanolithography", J. Phys. D: Appl. Phys. **53**, 055204 (2019).
- <sup>100</sup>Z. Bouza, J. Scheers, A. N. Ryabtsev, R. Schupp, L. Behnke, C. Shah, J. Sheil, M. Bayraktar, J. R. Crespo López-Urrutia, W. Ubachs, R. Hoekstra, and O. O. Versolato, "EUV spectroscopy of Sn<sup>5+</sup>–Sn<sup>10+</sup> ions in an electron beam ion trap and laser-produced plasmas", J. Phys. B: At. Mol. Opt. Phys. **53**, 195001 (2020).

- <sup>101</sup>L. Oster, "Emission, absorption, and conductivity of a fully ionized gas at radio frequencies", Rev. Mod. Phys. **33**, 525–543 (1961).
- <sup>102</sup>H. A. Kramers, "XCIII. On the theory of X-ray absorption and of the continuous X-ray spectrum", Philos. Mag. 46, 836–871 (1923).
- <sup>103</sup>H. Mizoguchi, H. Nakarai, T. Abe, K. M. Nowak, Y. Kawasuji, H. Tanaka, Y. Watanabe, T. Hori, T. Kodama, Y. Shiraishi, T. Yanagida, G. Soumagne, T. Yamada, T. Yamazaki, and T. Saitou, "High power LPP-EUV source with long collector mirror lifetime for high volume semiconductor manufacturing", in Proc. CSTIC 2018 (IEEE, 2018), 1–7.
- <sup>104</sup>K. Nishihara, A. Sunahara, A. Sasaki, M. Nunami, H. Tanuma, S. Fujioka, Y. Shimada, K. Fujima, H. Furukawa, T. Kato, F. Koike, R. More, M. Murakami, T. Nishikawa, V. Zhakhovskii, K. Gamata, A. Takata, H. Ueda, H. Nishimura, Y. Izawa, N. Miyanaga, and K. Mima, "Plasma physics and radiation hydrodynamics in developing an extreme ultraviolet light source for lithography", Phys. Plasmas 15, 056708 (2008).
- <sup>105</sup>S. Fujioka, M. Shimomura, Y. Shimada, S. Maeda, H. Sakaguchi, Y. Nakai, T. Aota, H. Nishimura, N. Ozaki, A. Sunahara, K. Nishihara, N. Miyanaga, Y. Izawa, and K. Mima, "Pure-tin microdroplets irradiated with double laser pulses for efficient and minimum-mass extreme-ultraviolet light source production", Appl. Phys. Lett. **92**, 241502 (2008).
- <sup>106</sup>R. Schupp, L. Behnke, J. Sheil, Z. Bouza, M. Bayraktar, W. Ubachs, R. Hoekstra, and O. O. Versolato, "Characterization of 1- and 2-μm-wavelength laserproduced microdroplet-tin plasma for generating extreme ultraviolet light", submitted.
- <sup>107</sup>L. Behnke, R. Schupp, Z. Bouza, M. Bayraktar, Z. Mazzotta, R. Meijer, J. Sheil, S. Witte, W. Ubachs, R. Hoekstra, and O. O. Versolato, "Extreme ultraviolet light from a tin plasma driven by a 2-μm-wavelength laser", Opt. Express **29**, 4475–4487 (2021).
- <sup>108</sup>H. Matsukuma, A. Sunahara, T. Yanagida, H. Tomuro, K. Kouge, T. Kodama, T. Hosoda, S. Fujioka, and H. Nishimura, "Correlation between laser absorption and radiation conversion efficiency in laser produced tin plasma", Appl. Phys. Lett. **107**, 121103 (2015).
- <sup>109</sup>T. Higashiguchi, N. Dojyo, M. Hamada, W. Sasaki, and S. Kubodera, "Low-debris, efficient laser-produced plasma extreme ultraviolet source by use of a regenerative liquid microjet target containing tin dioxide (SnO<sub>2</sub>) nanoparticles", Appl. Phys. Lett. **88**, 201503 (2006).
- <sup>110</sup>D. Nakamura, T. Akiyama, K. Okazaki, K. Tamaru, A. Takahashi, and T. Okada, "Ablation dynamics of tin micro-droplet irradiated by double pulse laser used

for extreme ultraviolet lithography source", J. Phys. D: Appl. Phys. **41**, 245210 (2008).

- <sup>111</sup>I. W. Choi, H. Daido, S. Yamagami, K. Nagai, T. Norimatsu, H. Takabe, M. Suzuki, T. Nakayama, and T. Matsui, "Detailed space-resolved characterization of a laserplasma soft-x-ray source at 13.5-nm wavelength with tin and its oxides", J. Opt. Soc. Am. B **17**, 1616–1625 (2000).
- <sup>112</sup>B. Liu, D. Kurilovich, H. Gelderblom, and O. O. Versolato, "Mass Loss from a Stretching Semitransparent Sheet of Liquid Tin", Phys. Rev. Appl. **13**, 024035 (2020).
- <sup>113</sup>B. Liu, R. A. Meijer, J. Hernandez-Rueda, D. Kurilovich, Z. Mazzotta, S. Witte, and O. O. Versolato, "Laser-induced vaporization of a stretching sheet of liquid tin", accepted (2021).
- <sup>114</sup>G. D. O'Sullivan and R. Faulkner, "Tunable narrowband soft x-ray source for projection lithography", Opt. Eng. **33**, 3978–3984 (1994).
- <sup>115</sup>T. Sizyuk and A. Hassanein, "Tuning laser wavelength and pulse duration to improve the conversion efficiency and performance of EUV sources for nano-lithography", Phys. Plasmas **27**, 103507 (2020).

# List of publications

#### Chapter 1

**R. Schupp**, F. Torretti, R. A. Meijer, M. Bayraktar, J. Scheers, D. Kurilovich, A. Bayerle, K. S. E. Eikema, S. Witte, W. Ubachs, R. Hoekstra, and O. O. Versolato, "Efficient generation of extreme ultraviolet light from Nd:YAG-driven microdroplettin plasma", Phys. Rev. Appl. **12**, 014010 (2019)

#### Chapter 2

**R. Schupp**, F. Torretti, R. A. Meijer, M. Bayraktar, J. Sheil, J. Scheers, D. Kurilovich, A. Bayerle, A. A. Schafgans, M. Purvis, K. S. E. Eikema, S. Witte, W. Ubachs, R. Hoekstra, and O. O. Versolato, "Radiation transport and scaling of optical depth in Nd:YAG laser-produced microdroplet-tin plasma", Appl. Phys. Lett. **115**, 124101 (2019)

#### Chapter 3

L. Behnke, **R. Schupp**, Z. Bouza, M. Bayraktar, Z. Mazzotta, R. Meijer, J. Sheil, S. Witte, W. Ubachs, R. Hoekstra, and O. O. Versolato, "Extreme ultraviolet light from a tin plasma driven by a  $2-\mu$ m-wavelength laser", Opt. Express **29**, 4475-4487 (2021)

#### Chapter 4

**R. Schupp**, L. Behnke, J. Sheil, Z. Bouza, M. Bayraktar, W. Ubachs, R. Hoekstra, and O. O. Versolato, "Characterization of 1- and  $2-\mu$ m-wavelength laser-produced microdroplet-tin plasma for generating extreme ultraviolet light", submitted

#### Chapter 5

**R. Schupp**, L. Behnke, Z. Bouza, J. Sheil, M. Bayraktar, W. Ubachs, R. Hoekstra, and O. O. Versolato, "Characterization of angularly resolved EUV emission from 2-µm-wavelength laser-driven Sn plasma using preformed liquid disk targets", to be submitted

The author also contributed to the following publications:

- F. Torretti, J. Sheil, R. Schupp, M. M. Basko, M. Bayraktar, R. A. Meijer, S. Witte, W. Ubachs, R. Hoekstra, O. O. Versolato, A. J. Neukirch, and J. Colgan, "Prominent radiative contributions from multiply-excited states in laser-produced tin plasma for nanolithography", Nat. Commun. 11, 2334 (2020)
- J. Scheers, R. Schupp, R. Meijer, W. Ubachs, R. Hoekstra, and O. O. Versolato, "Time- and space-resolved optical Stark spectroscopy in the afterglow of laserproduced tin-droplet plasma", Phys. Rev. E 102, 013204 (2020)
- Z. Bouza, J. Scheers, A. Ryabtsev, R. Schupp, L. Behnke, C. Shah, J. Sheil, M. Bayraktar, J. R. Crespo López-Urrutia, W. Ubachs, R. Hoekstra, and O. O. Versolato, "EUV spectroscopy of Sn<sup>5+</sup>–Sn<sup>10+</sup> ions in an electron beam ion trap and laser-produced plasmas", J. Phys. B: At. Mol. Opt. Phys. 53, 195001 (2020)
- R. A. Meijer, R. Schupp, J. Sheil, K. S. E. Eikema, O. O. Versolato, and S. Witte, "Spall velocity reduction in double-pulse impact on tin microdroplets", submitted
- F. Torretti, R. Schupp, D. Kurilovich, A. Bayerle, J. Scheers, W. Ubachs, R. Hoekstra, and O. O. Versolato, "Short-wavelength out-of-band EUV emission from Sn laser-produced plasma", J. Phys. B: At. Mol. Opt. Phys. 51, 045005 (2018)
- D. Kurilovich, M. M. Basko, D. A. Kim, F. Torretti, R. Schupp, J. C. Visschers, J. Scheers, R. Hoekstra, W. Ubachs, and O. O. Versolato, "Power-law scaling of plasma pressure on laser-ablated tin microdroplets", Phys. Plasmas 25, 012709 (2018)
- D. Kurilovich, T. de F. Pinto, F. Torretti, R. Schupp, J. Scheers, A. S. Stodolna, H. Gelderblom, K. S. E. Eikema, S. Witte, W. Ubachs, R. Hoekstra, and O. O. Versolato, "Expansion dynamics after laser-induced cavitation in liquid tin microdroplets", Phys. Rev. Appl. 10, 054005 (2018).
- J. Scheers, A. Ryabtsev, A. Borschevsky, J. C. Berengut, K. Haris, R. Schupp, D. Kurilovich, F. Torretti, A. Bayerle, E. Eliav, W. Ubachs, O. O. Versolato, and R. Hoekstra, "Energy level structure of Sn<sup>3+</sup> ions", Phys. Rev. A 98, 062503 (2018)

In addition to these publications, the work presented in this thesis resulted in 7 application ideas shared with ASML.

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